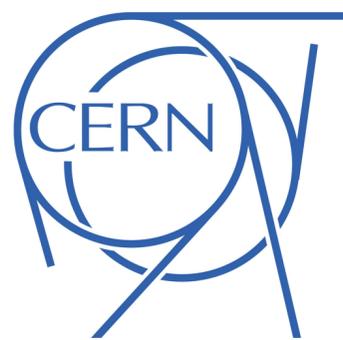


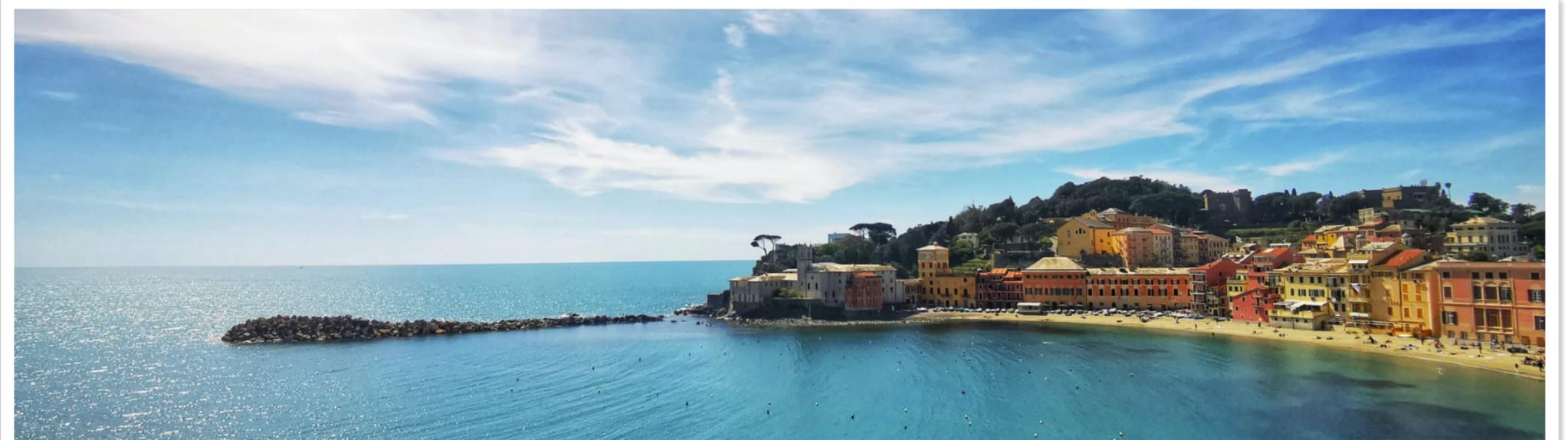
Development of the radiation-hard MALTA CMOS sensor for tracking applications

Giuliano Gustavino

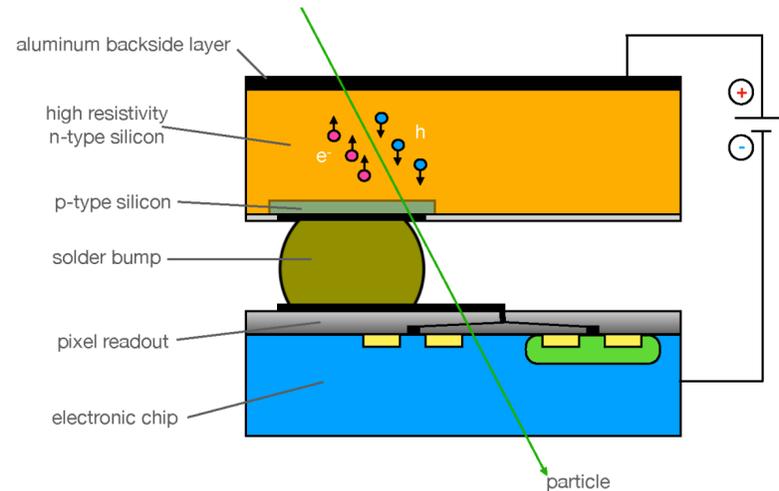
Phil Allport, Ignacio Asensi Tortajada, Prafulla Behera, Dumitru Vlad Berlea, Daniela Bortoletto, Craig Buttar, Florian Dachs, Valerio Dao, Ganapati Dash, Dominik Dobrijević, Lucian Fasselt, Leyre Flores Sanz de Acedo, Andrea Gabrielli, Martin Gaži, Vicente González, Giuliano Gustavino, Pranati Jana, Heinz Pernegger, Francesco Piro, Petra Riedler, Milou van Rijnbach, Heidi Sandaker, Carlos Solans Sánchez, Walter Snoeys, Tomislav Suligoj, Marcos Vázquez Núñez, Anusree Vijay, Julian Weick, Steven Worm, Abdelhak M. Zoubir



16 – 20 October 2023



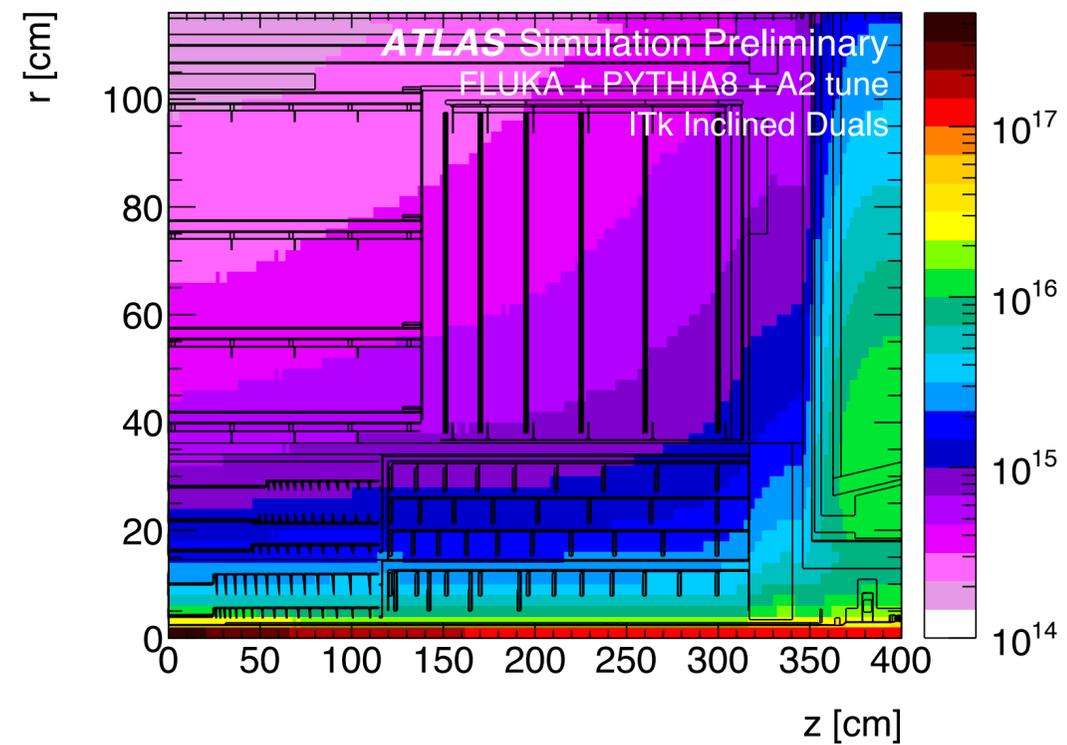
Motivation for Monolithic Pixel Sensors



Hybrid detectors (ASIC bump-bonded to sensor) are the most adopted and field-tested solution

Challenging requirements for future collider experiments:

- Extreme radiation tolerance
- Large hit rate
- High granularity
- Fast response time
- Large surface
- Very thin



Si 1 MeV neutron eq. fluence [$\text{cm}^{-2} / 4000\text{fb}^{-1}$]

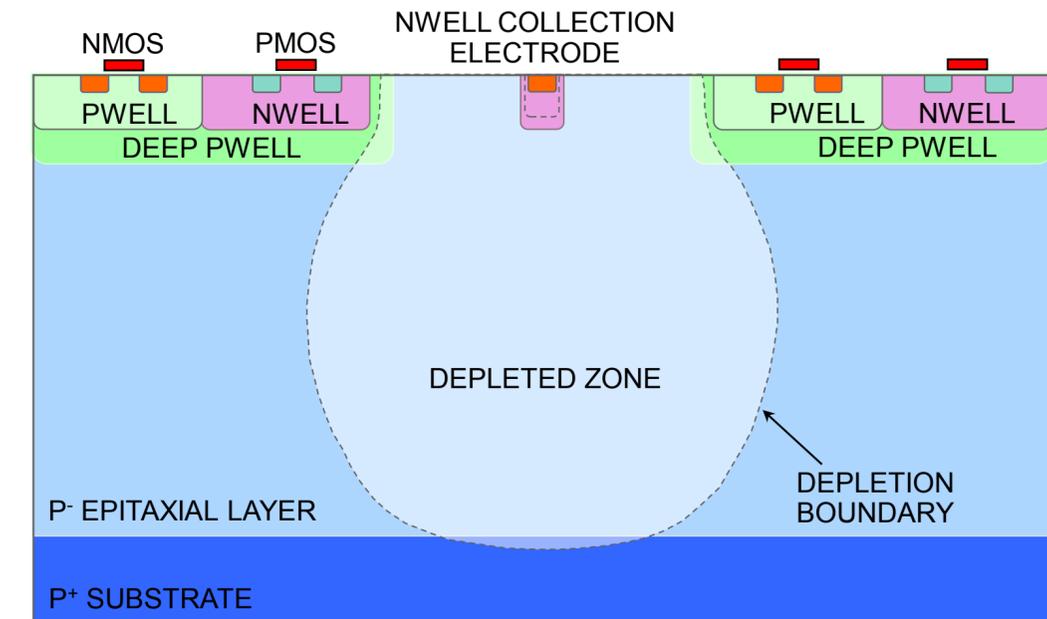


MAPS (Monolithic Active Pixel Sensors)



- * ASICs and sensor on the same substrate
 - ▶ avoid custom bump bonding
 - ▶ reduced production effort
- * industrial-like CMOS production process
 - ▶ reduced costs
 - ▶ large area detectors
- * low mass / high granularity detectors
 - ▶ reduced material
- * small capacitance
 - ▶ large signal/noise ratio
- ◆ still in R&D phase for HEP
 - ▶ in particular for what concerns radiation hardness

A MALTA ancestor:
ALPIDE - ALICE ITS



Charge collection time ~ 100 ns via diffusion

A MALTA cousin:

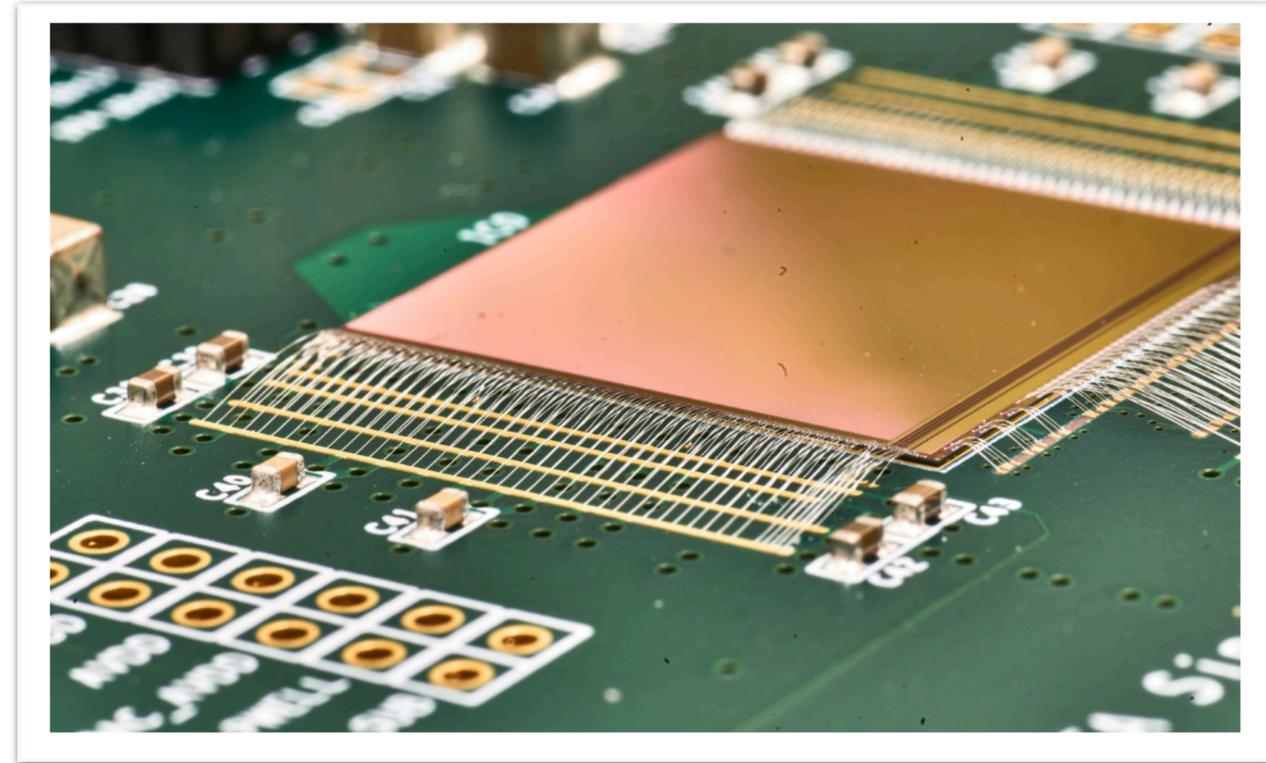
TJ-MonoPix

see [*L. Schall' slides*](#) for details

MALTA chip

- * Full scale demonstrator*

- ▶ 180 nm Tower CMOS imaging technology
- ▶ 2x2 cm²
- ▶ 512 x 512 pixels



- * Originally conceived for ATLAS pixel detector upgrade for HL-LHC:

- ▶ radiation hard up to **1.5 x 10¹⁵ n_{eq}/cm²**
- ▶ timing response: **within 25 ns**



- ◆ ALPIDE: < 10¹⁴ n_{eq}/cm²
- ◆ ALPIDE: several μsec

- * **Asynchronous readout architecture**

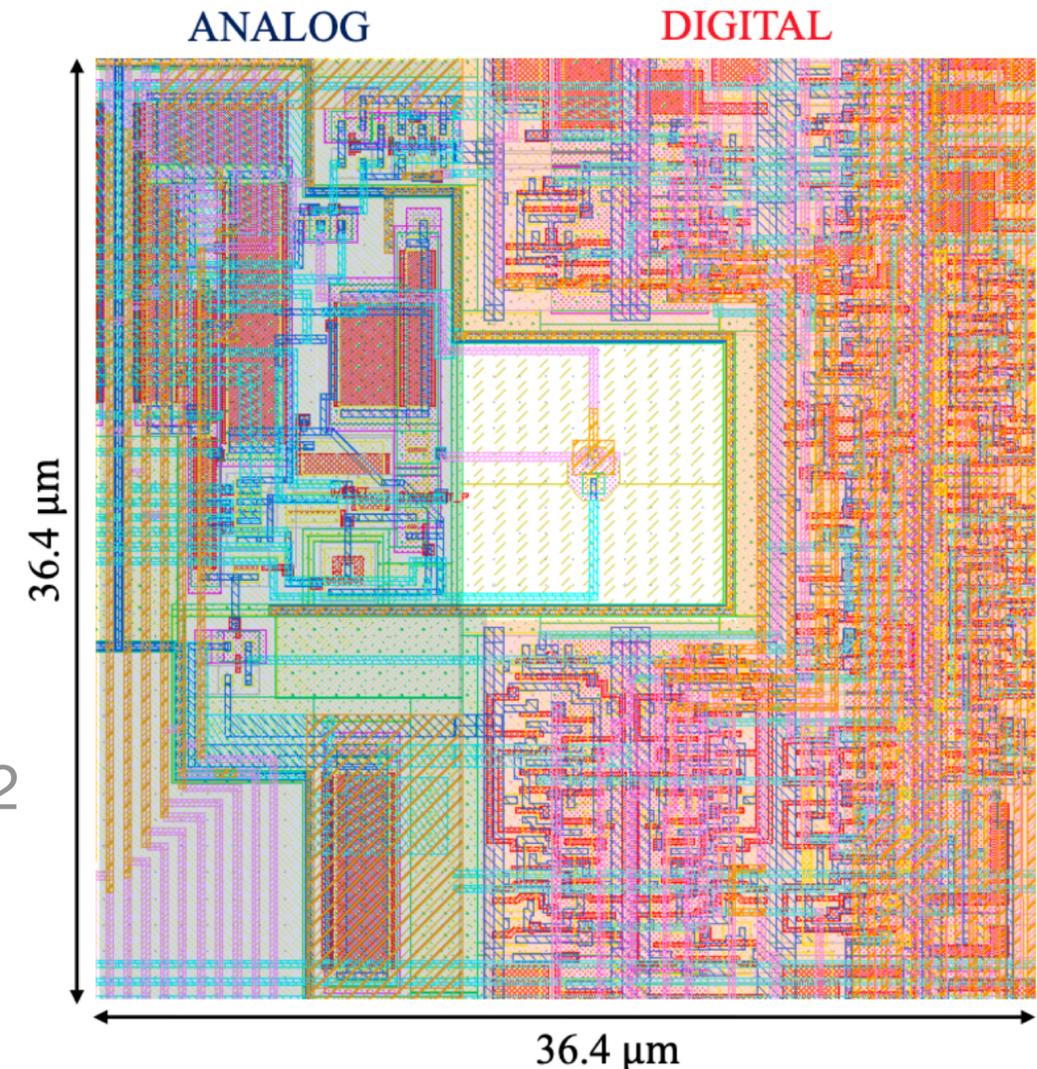
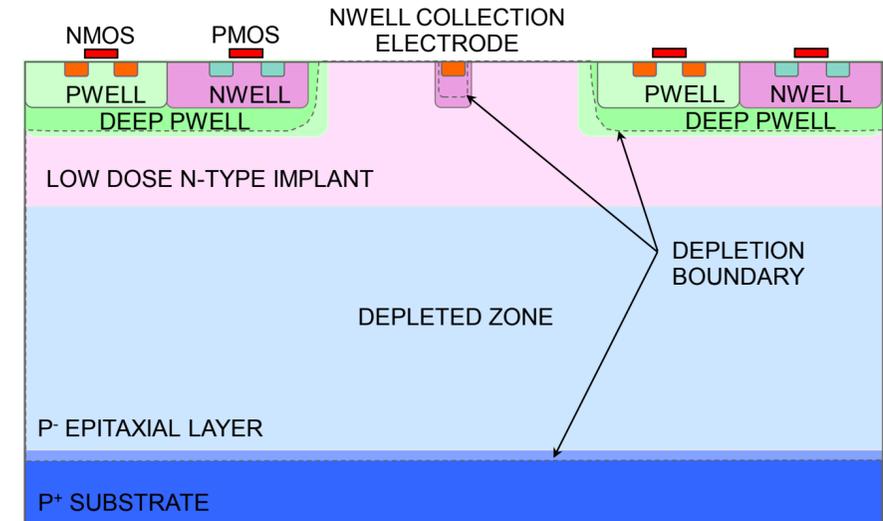
- ▶ no time-over-threshold information
- ▶ hit info directly transmitted from chip to periphery
- ▶ reduce power consumption and maintain hit-time information
 - high data rate (>100 MHz/cm²)

*

MALTA Pixel



- * pixel size $36.4 \times 36.4 \mu\text{m}^2$ → ♦ ATLAS ITkPIX: $50 \times 50 \mu\text{m}^2$
- * thickness down to $50 \mu\text{m}$ → ♦ ATLAS ITkPIX: $\sim 100 \div 150 \mu\text{m}$
 - ▶ available also with 100 and 300 μm
- * $3 \times 3 \mu\text{m}^2$ collection electrode
 - ▶ minimal capacitance ($< 5 \text{ fF}$)
 - $\text{ENC} < 15 e^-$
- * low voltage ($6 \div 55 \text{ V}$) → ♦ ATLAS ITkPIX: $80 \div 500 \text{ V}$
- * low power
 - ▶ $1 \mu\text{W}/\text{pixel}$
 - ▶ $70 \text{ mW}/\text{cm}^2$ analog power
 - ▶ $10 \text{ mW}/\text{cm}^2$ digital power

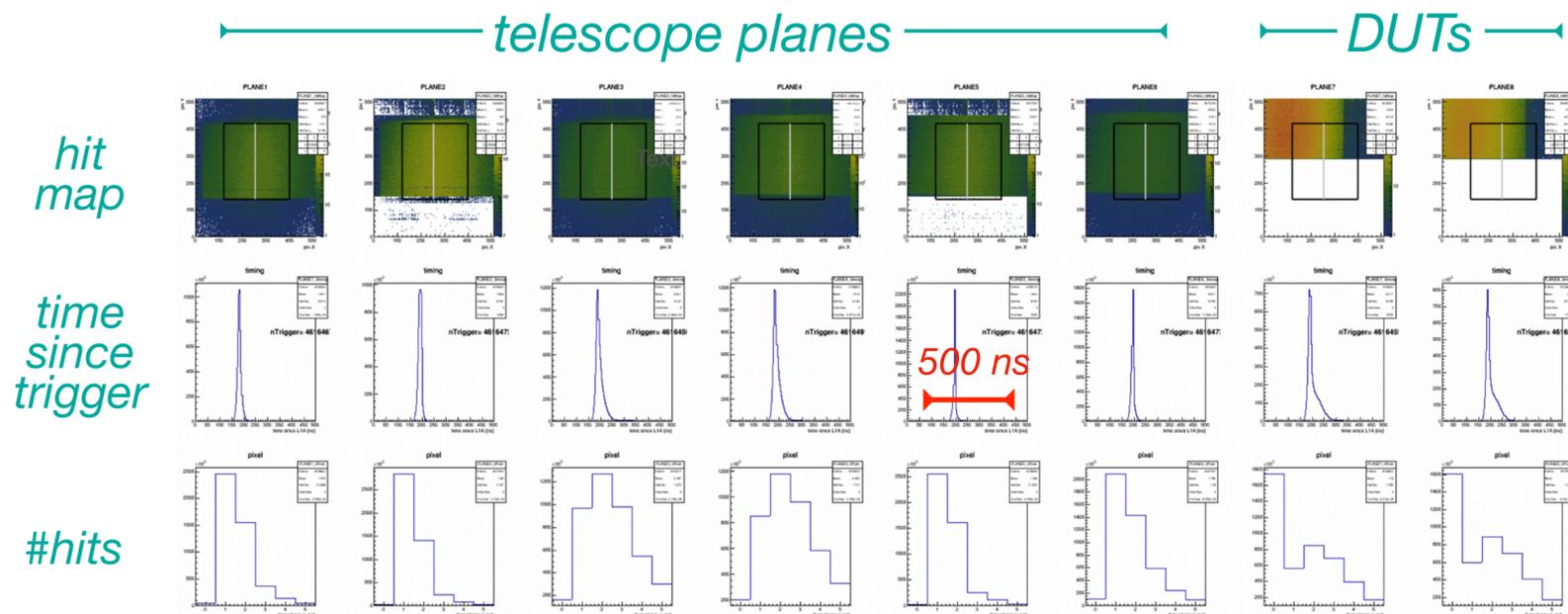
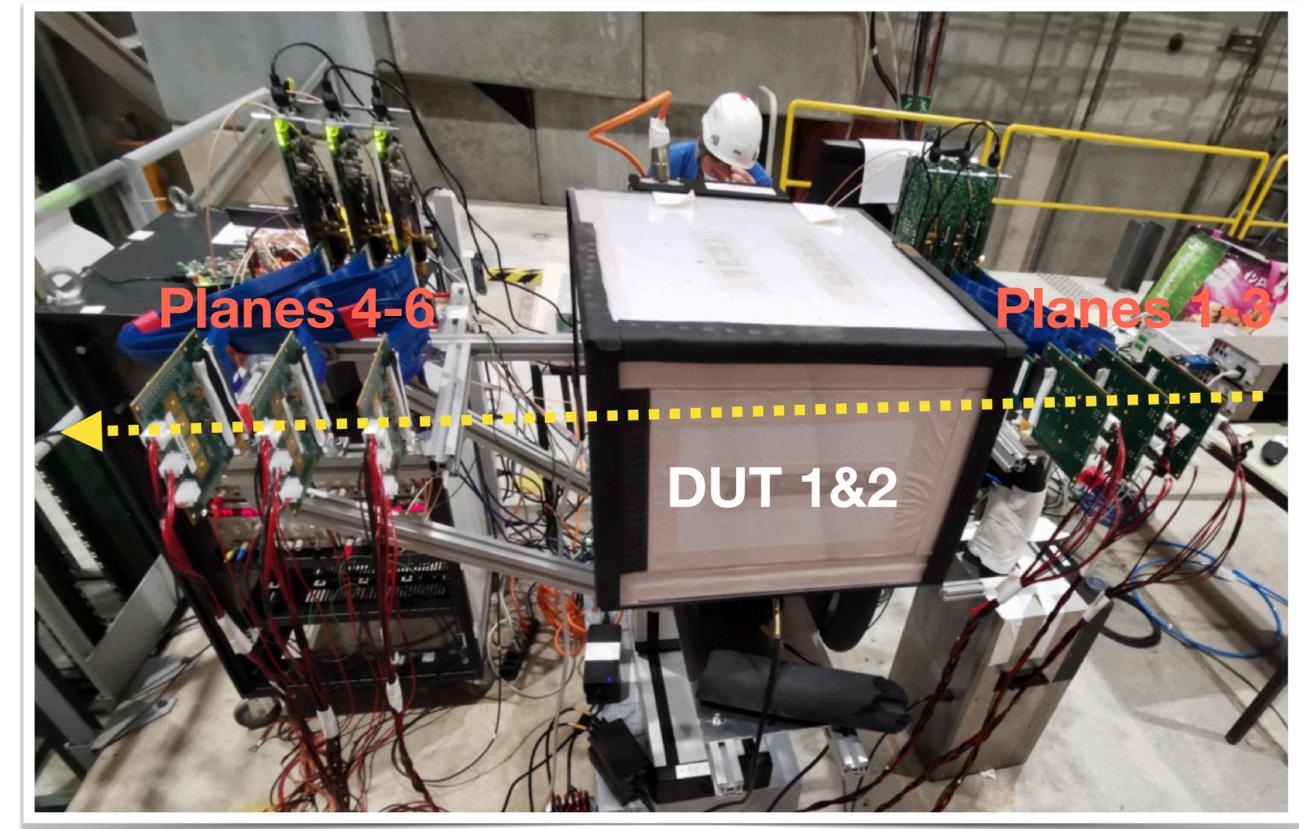
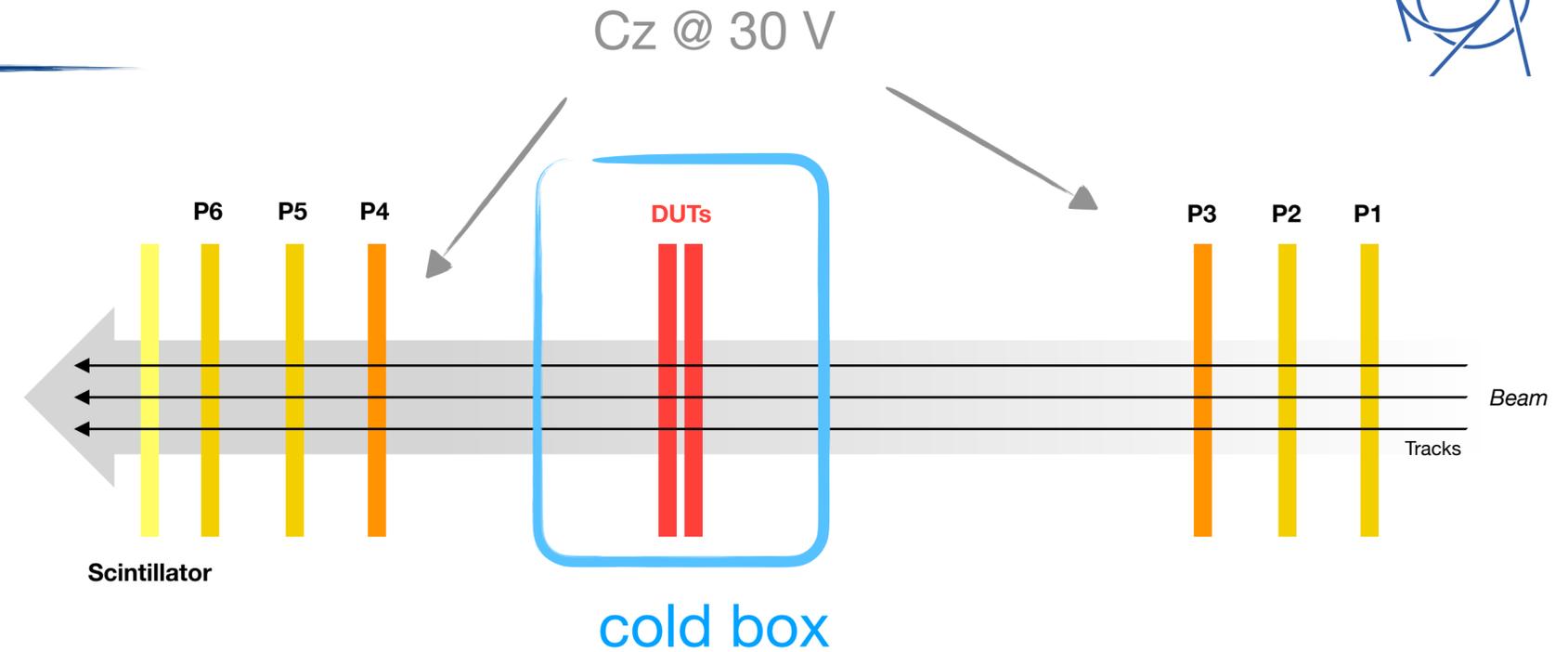


MALTA Telescope @ SPS

Dedicated beam telescope

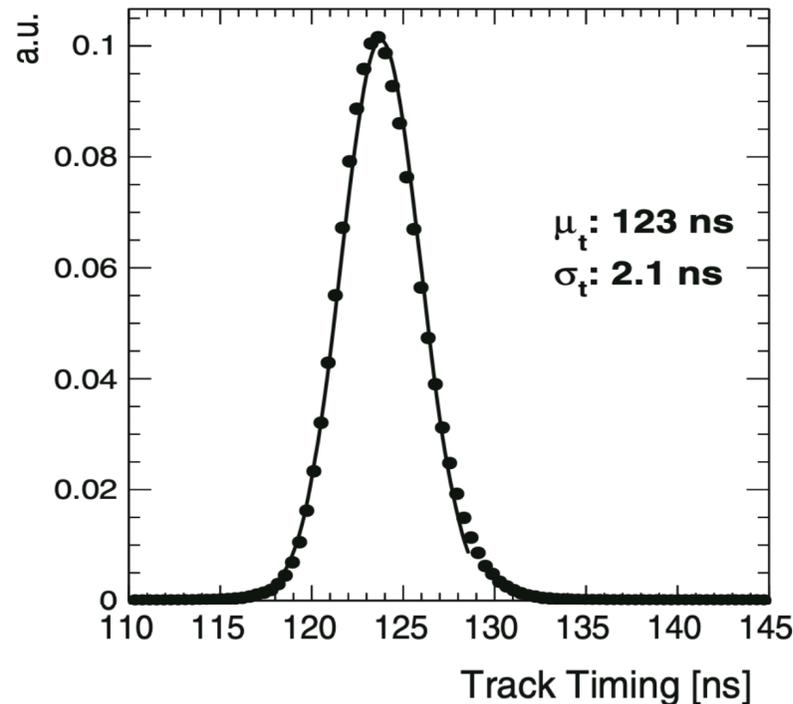
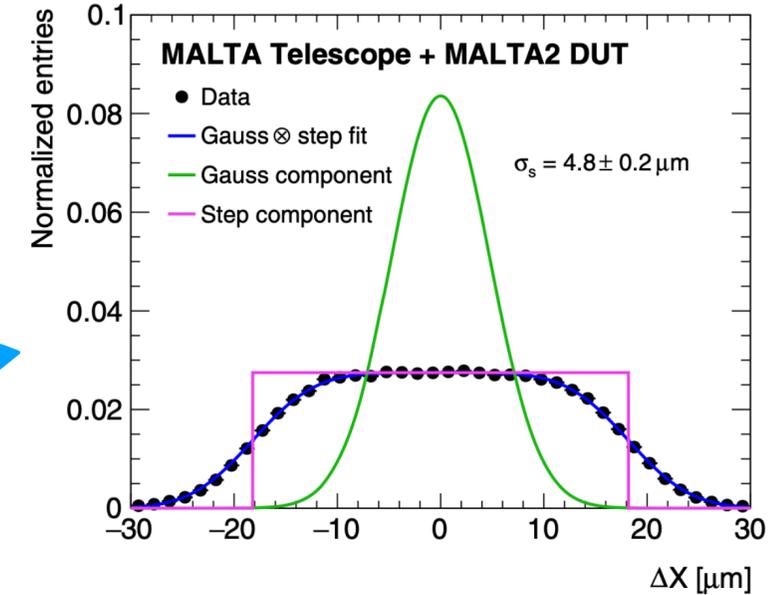
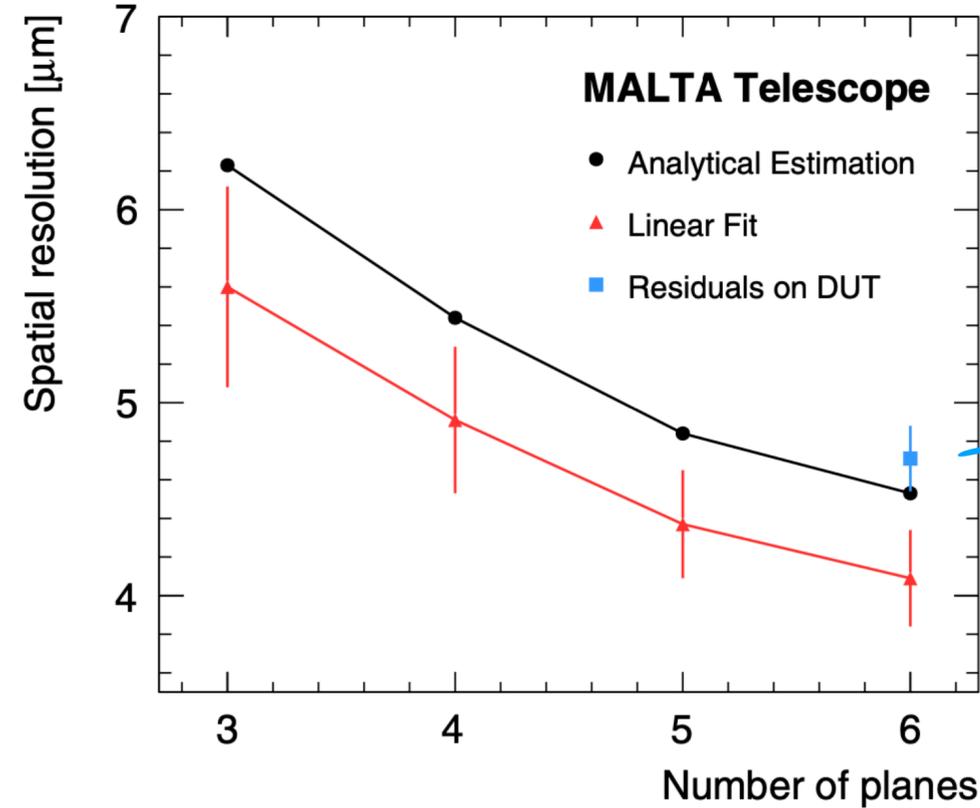
with 1st generation MALTA chips:

- * 6 tracking planes
 - ▶ internal Cz samples @ 30 V \Rightarrow *cl size* ~ 2
- * scintillator for precise timing reference
- * flexible TLU configurations & online monitoring
- * can host different DUT sizes
 - ▶ permanently installed at SPS



* Spatial resolution: $\sigma_s = 4.1 \mu\text{m}$

- ▶ larger cluster size improves the analytical estimation
- ▶ fit of gaus \otimes step $\sigma_s = 4.7 \mu\text{m}$ includes effects of inhomogeneity and time resolution at the edges of the DUT that are not taken into account



* average time resolution: $\sigma_t = 2.1 \text{ ns}$

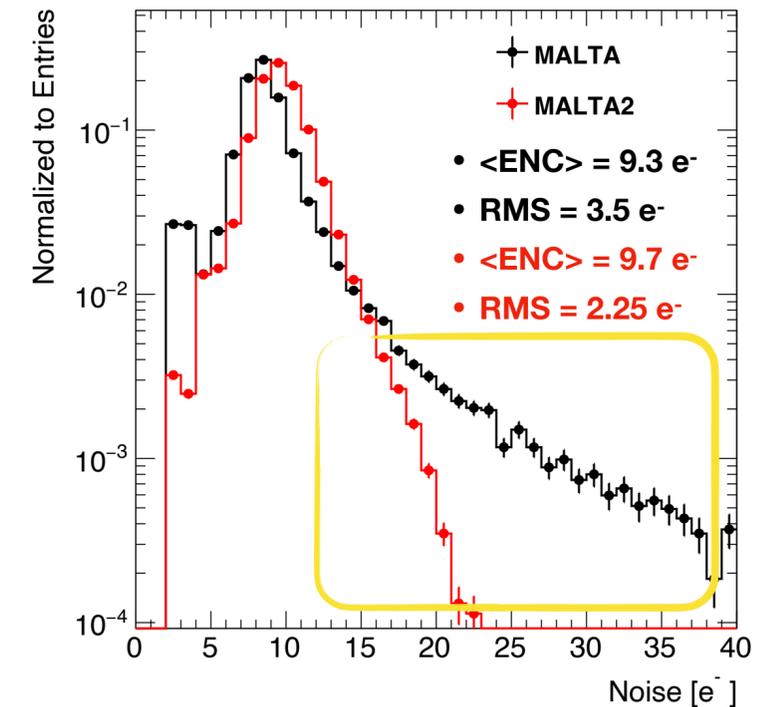
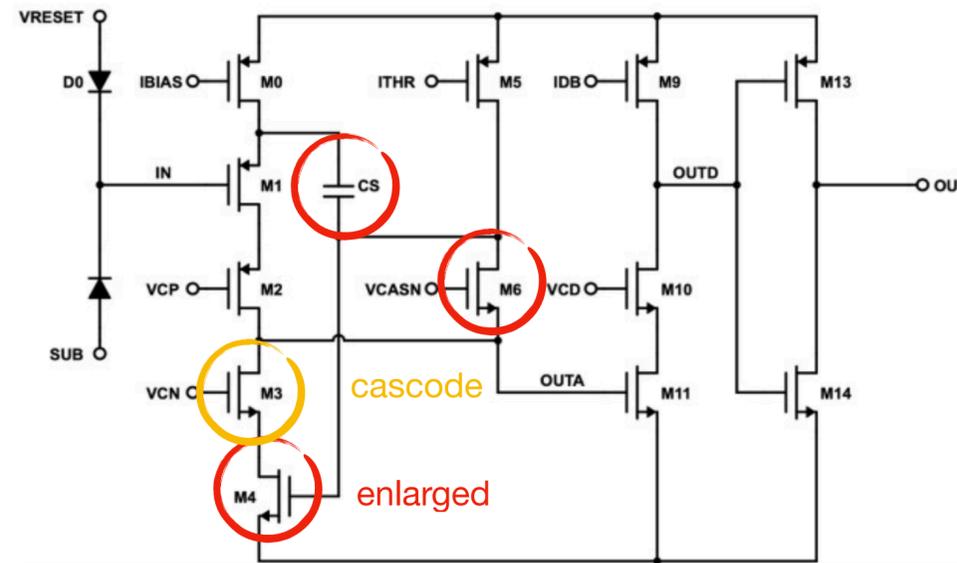
- ▶ allows it to operate at high rates
> 4×10^6 particles per spill

It is currently used to characterise MALTA chips, BCM', ITk pixels, HGDT's LGAD

MALTA2 processing

Improved the FE in MALTA2

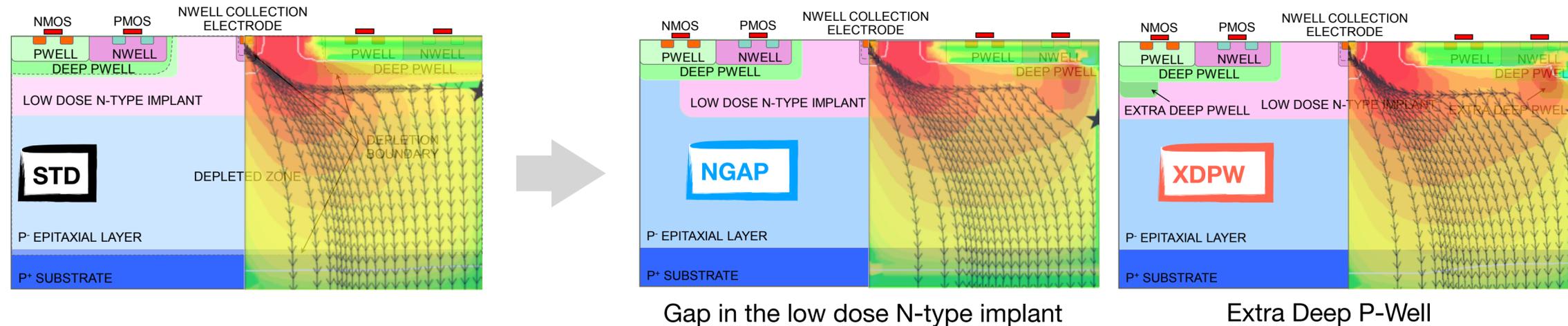
- ▶ enlarged transistors & cascode stage
- lower noise & higher gain



Process modifications

to increase lateral E-field in pixel corners

- * faster charge collection
- * No visible differences btw NGAP and XDPW



High resistivity (3-4 kΩcm) **Czochralski substrate**

- * larger depleted region with increasing substrate voltage
- * larger cluster size
- * larger radiation resistance

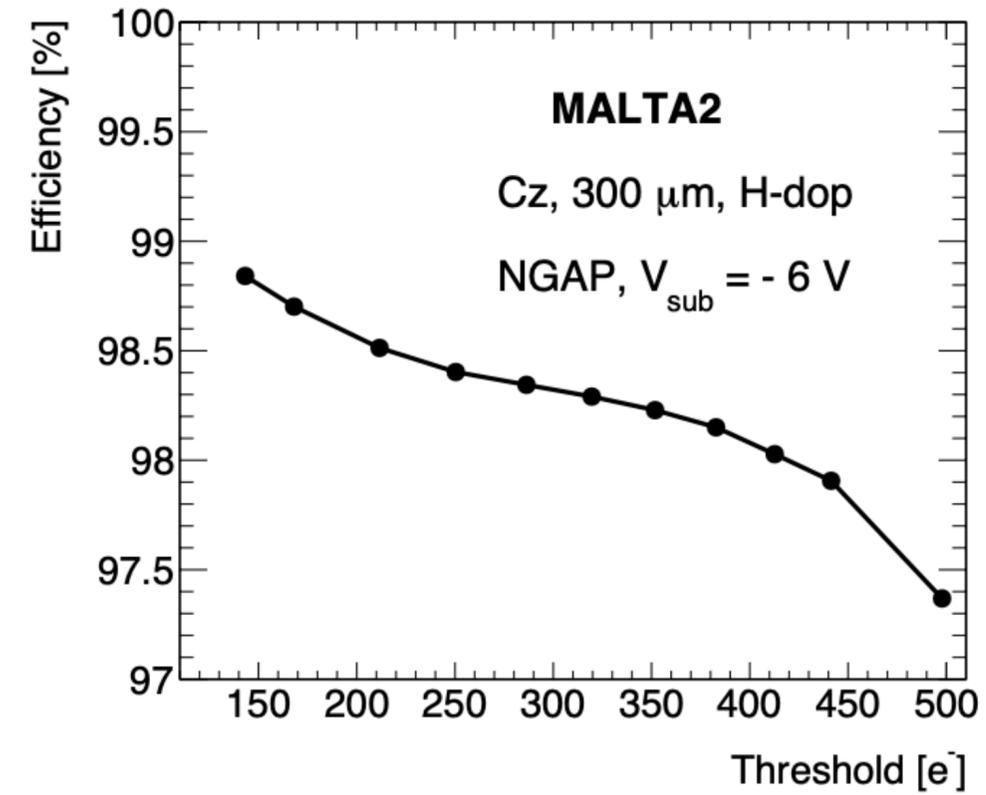
Backside metallisation

- guarantees a good propagation of the bias voltage across the whole chip
- * better performing than conductive glue

Efficiency

BEFORE irradiation

Full efficiency (~99%) at 150 e⁻ thresholds
at substrate voltage $V_{\text{SUB}} = -6$ V



Efficiency



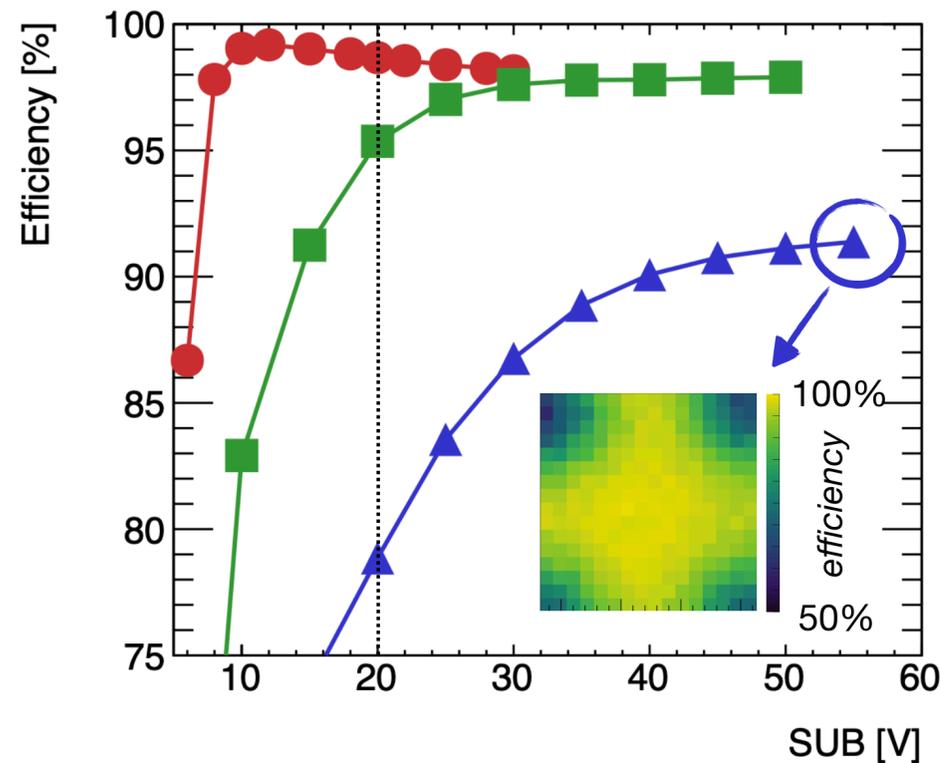
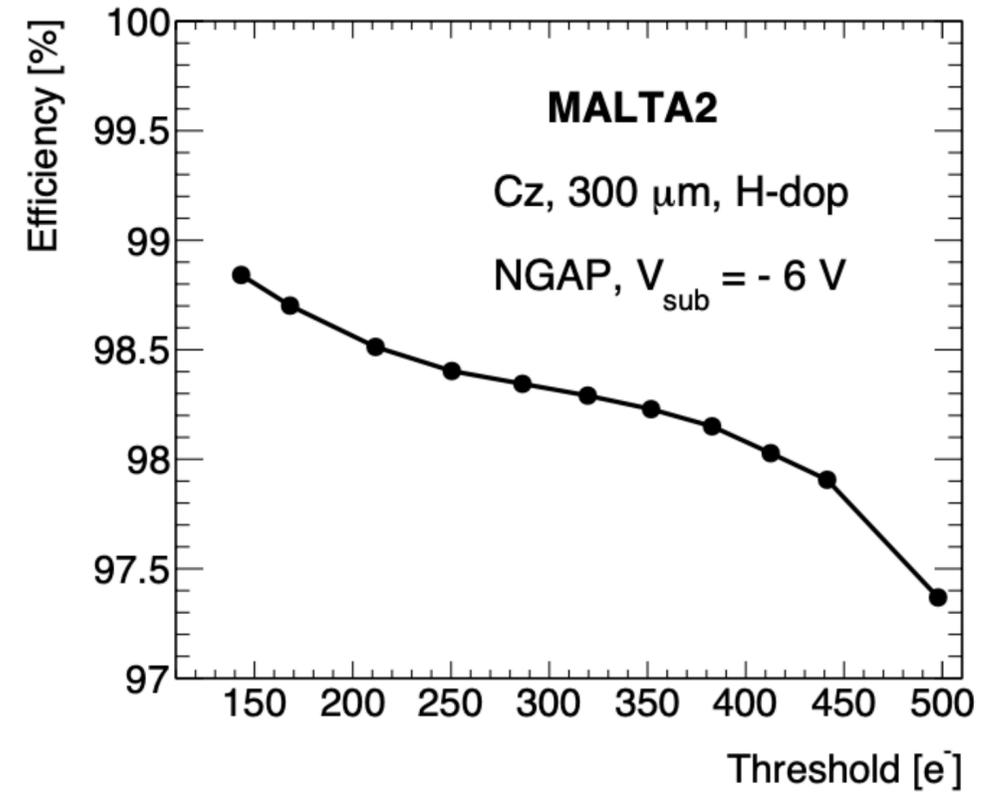
BEFORE irradiation

Full efficiency (~99%) at 150 e⁻ thresholds at substrate voltage $V_{SUB} = -6$ V

AFTER irradiation

> 95% efficiencies up to 2×10^{15} n_{eq}/cm²

* at substrate voltage ~20 V



Efficiency



BEFORE irradiation

Full efficiency (~99%) at 150 e⁻ thresholds at substrate voltage V_{SUB} = -6 V

AFTER irradiation

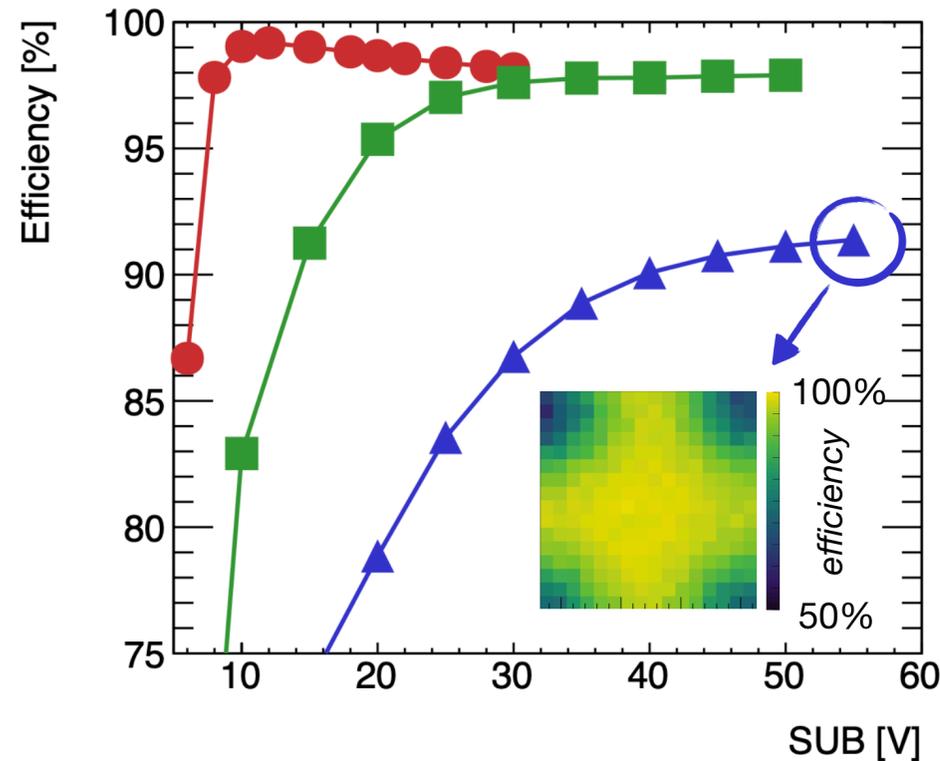
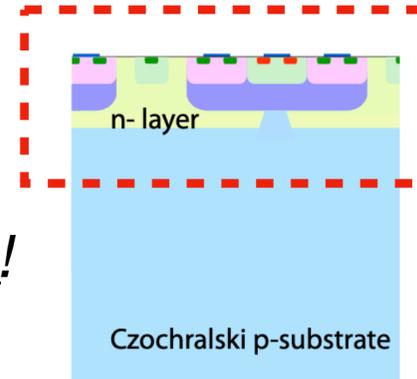
3x10¹⁵

> 95% efficiencies up to 2x10¹⁵ n_{eq}/cm²

- * at substrate voltage ~20 V
- * with higher doping on continuous n-layer*

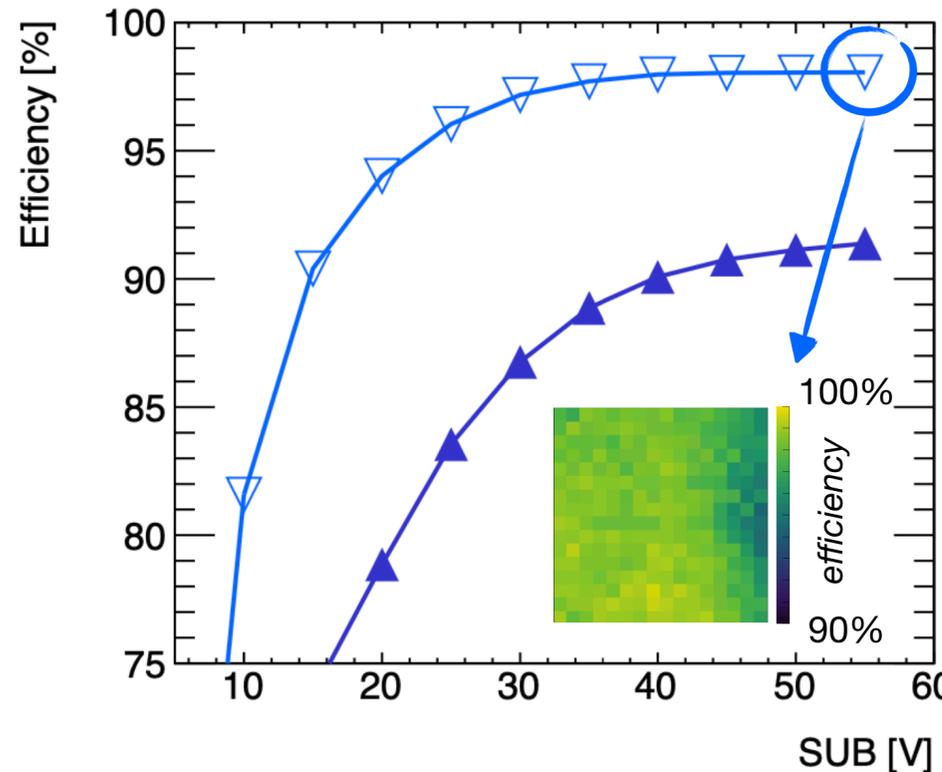


help recovering efficiency on the pixel corners!



MALTA2
Cz, 100 μm, H-dop
back-metal, XDPW

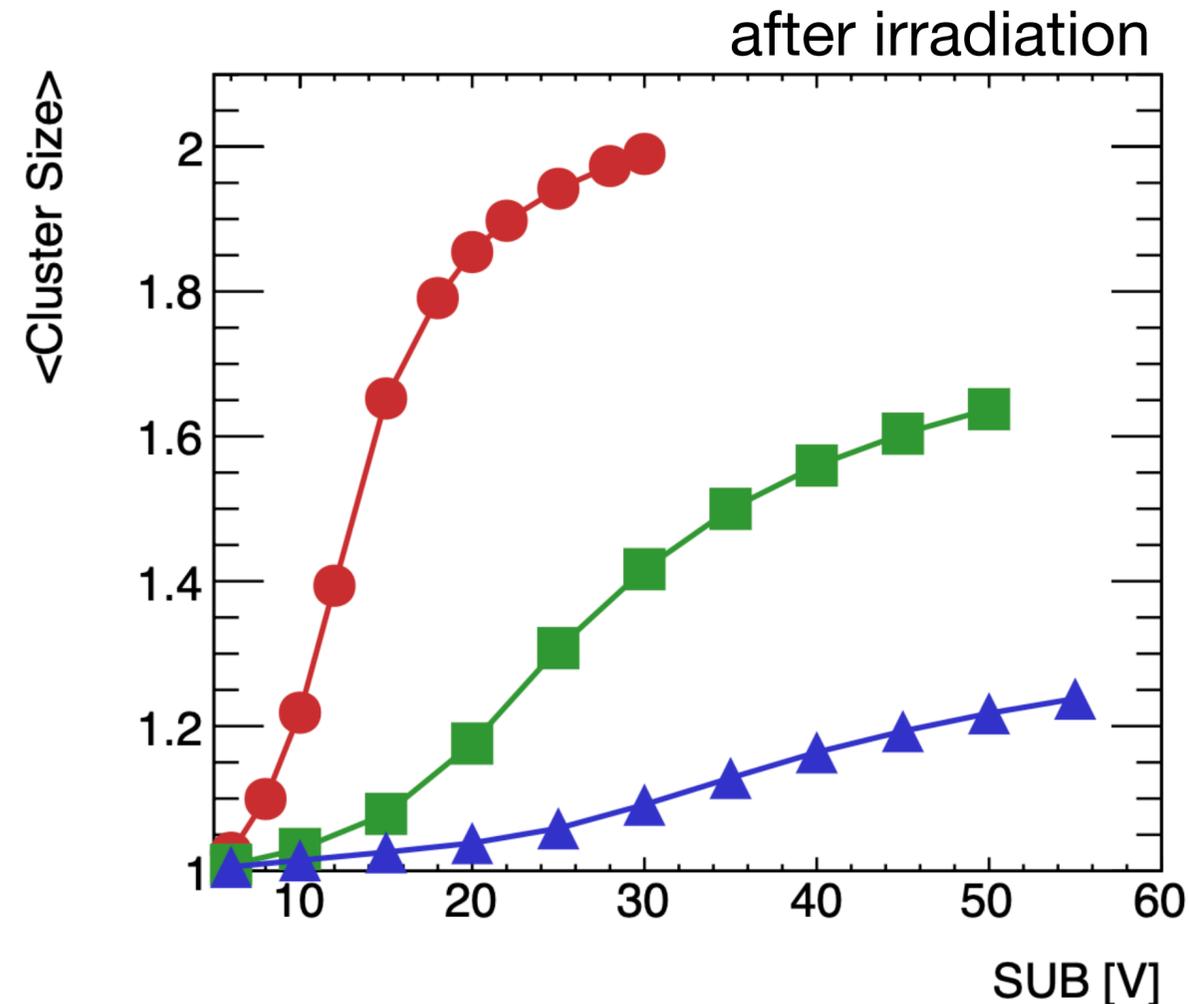
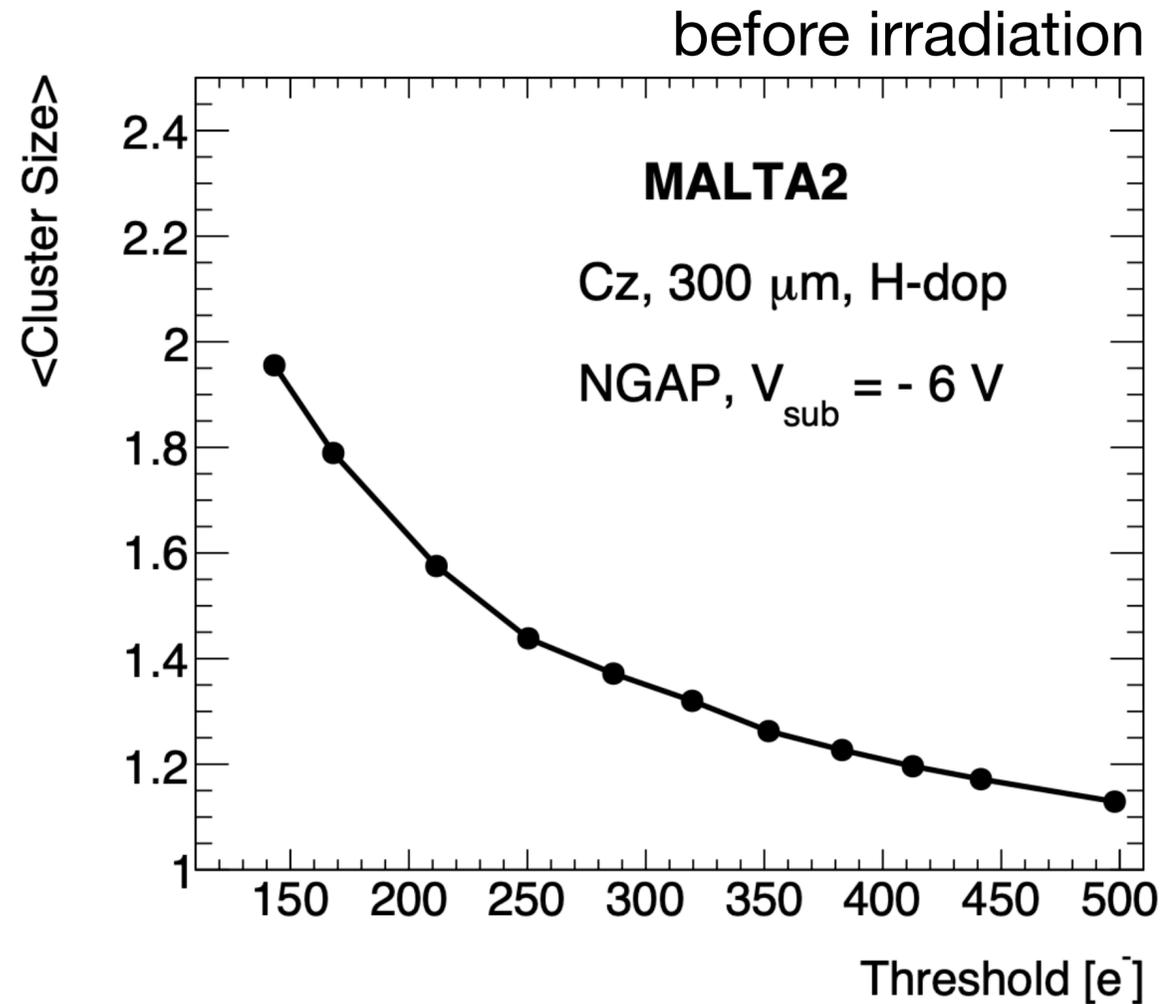
- 1x10¹⁵ 1 MeV n_{eq}/cm²
- 2x10¹⁵ 1 MeV n_{eq}/cm²
- ▲ 3x10¹⁵ 1 MeV n_{eq}/cm²



MALTA2
Cz, 100 μm
back-metal, XDPW
3x10¹⁵ 1 MeV n_{eq}/cm²

- ▽ VH-dop
- ▲ H-dop

*the doping level refers to the relative difference in implantation dose, approximately 70%.



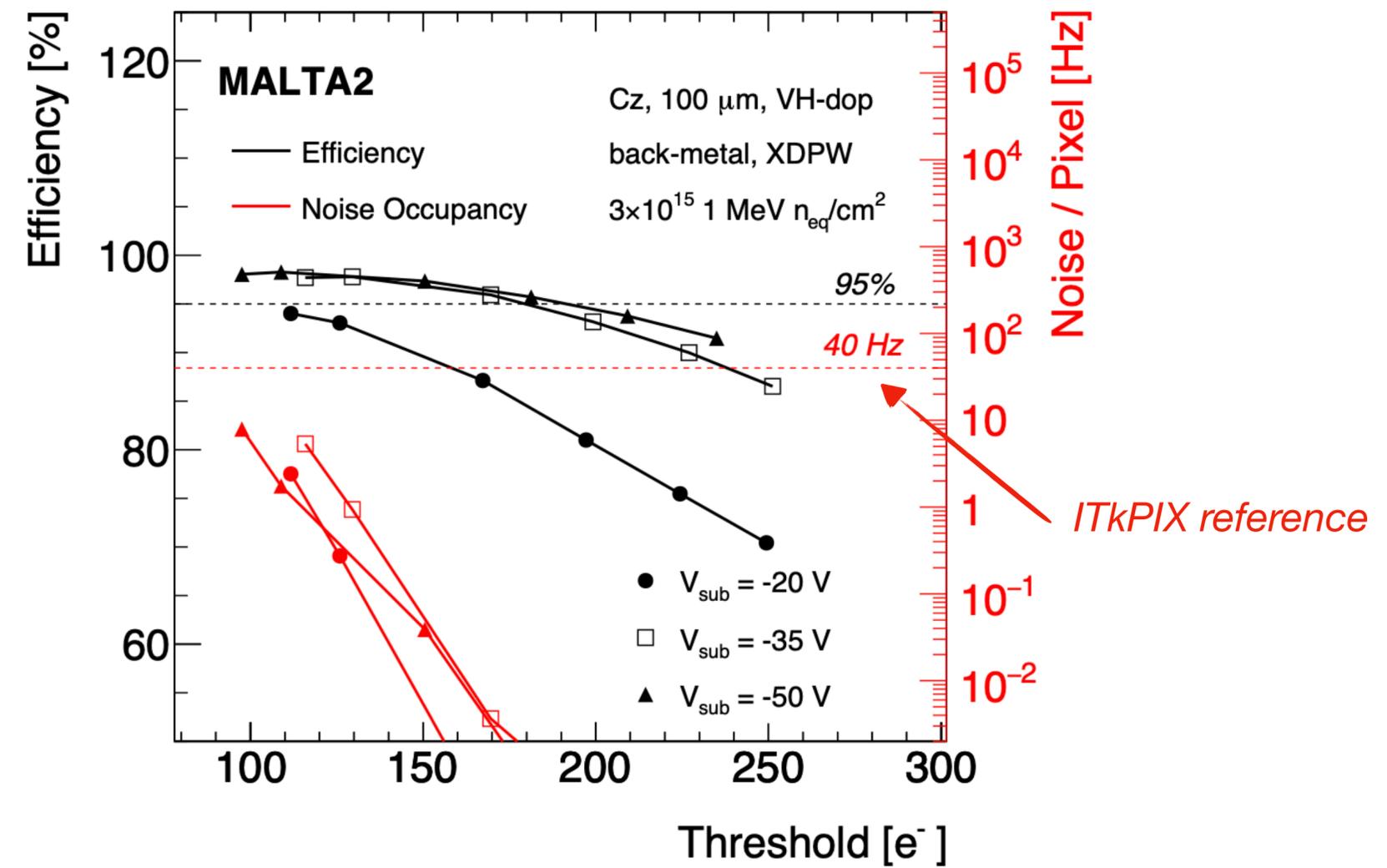
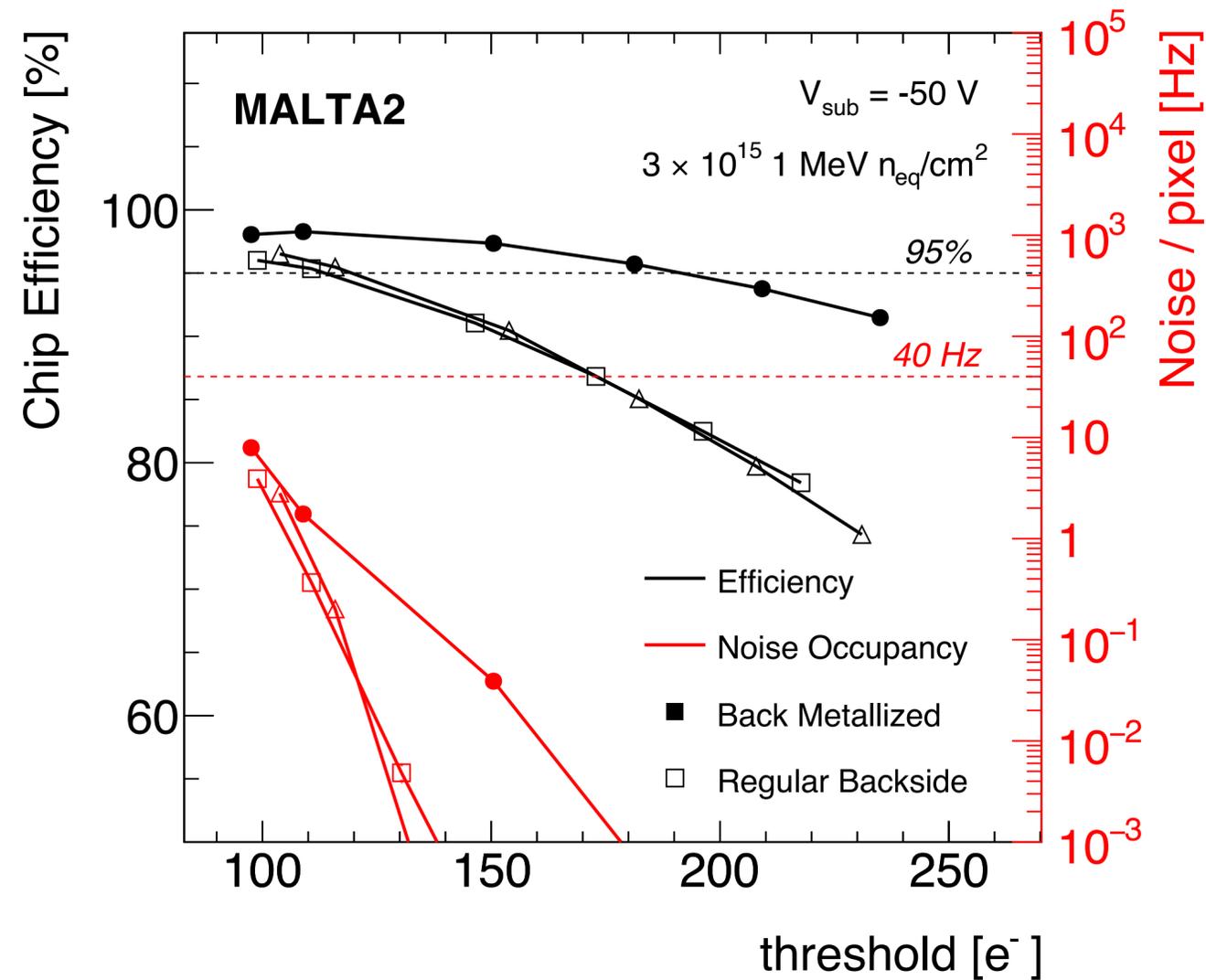
The cluster size increases for **lower thresholds** and **higher substrate voltages**

- enhanced charge-sharing effect btw pixels for larger active depths

Operational Window



Full efficiency after $3 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$ with backside metallisation at $\sim -30 \text{ V}$ substrate bias on VH-doped sensors
with a small noise occupancy

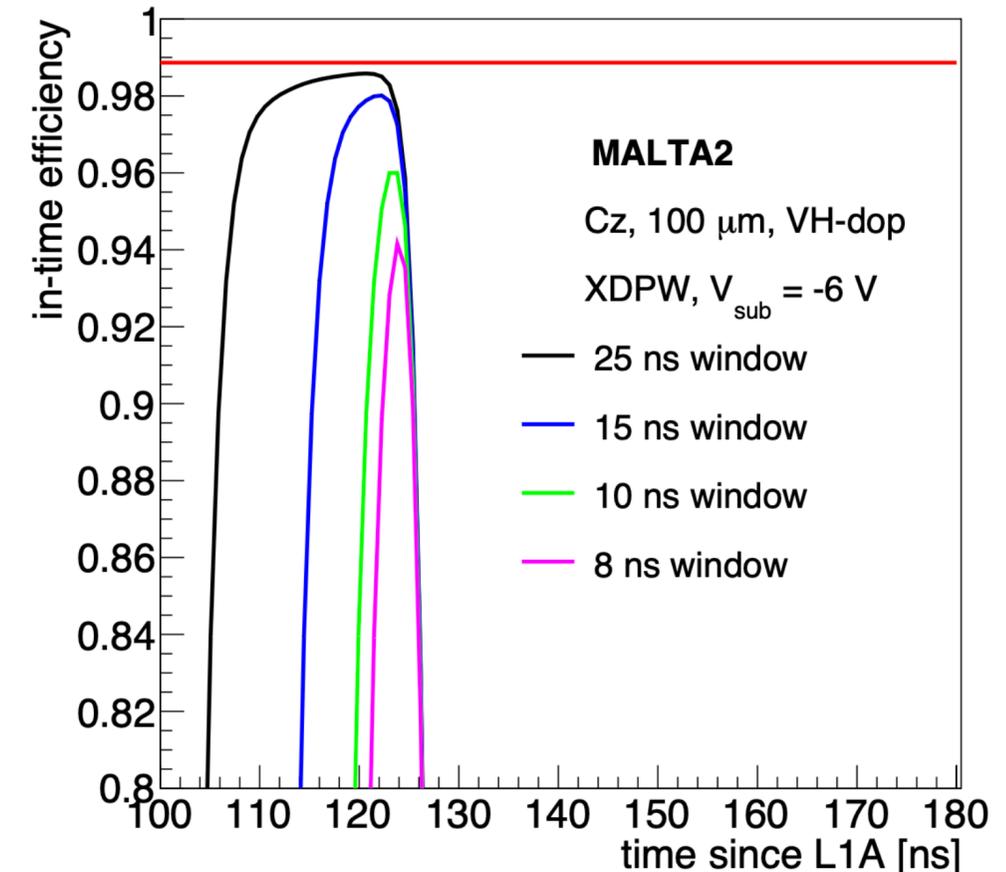
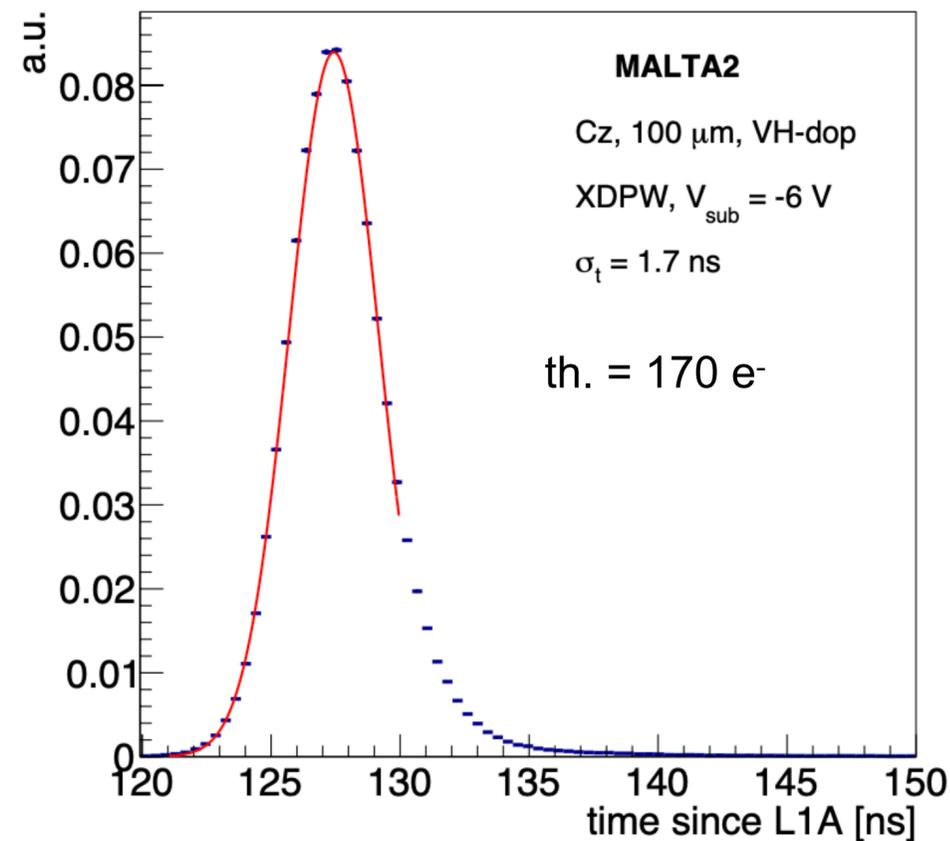


Backside metallisation allows propagating the bias voltage over the entire chip* and improves the performance

*A fiducial region (5% of the matrix) for regular backside sample is shown

Timing - before irradiation

Time of arrival of leading hit in the cluster wrt the scintillator reference



After signal propagation correction

✓ time resolution is $\sigma_t \sim 1.7 \text{ ns}$

Convolution of:

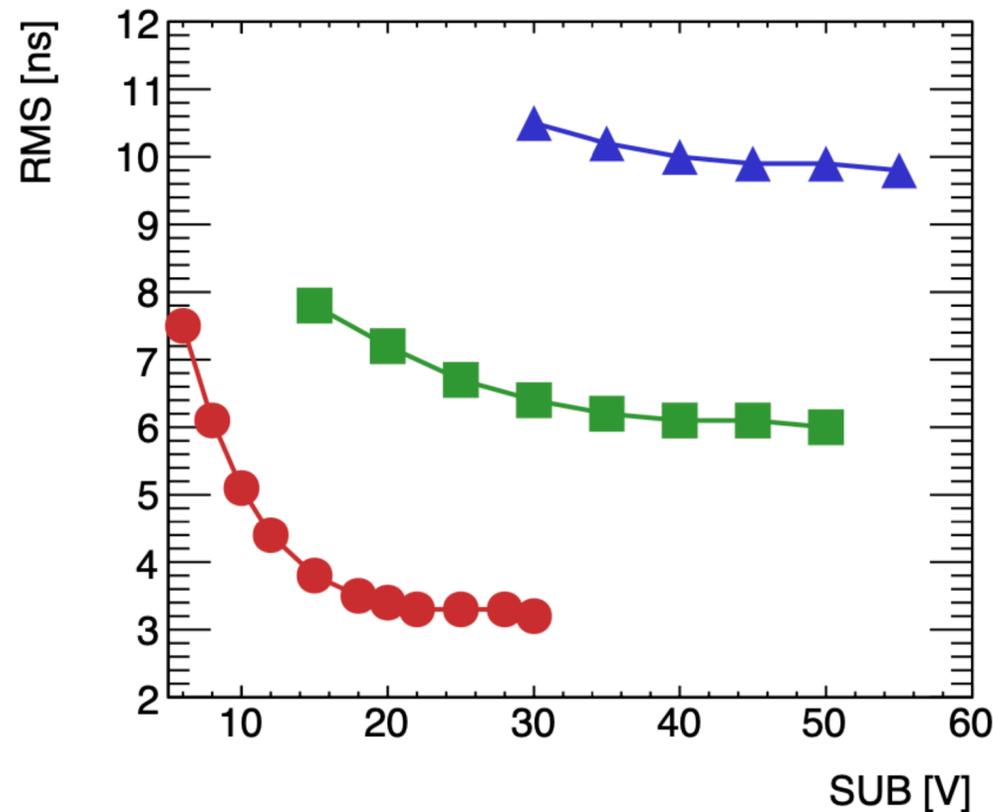
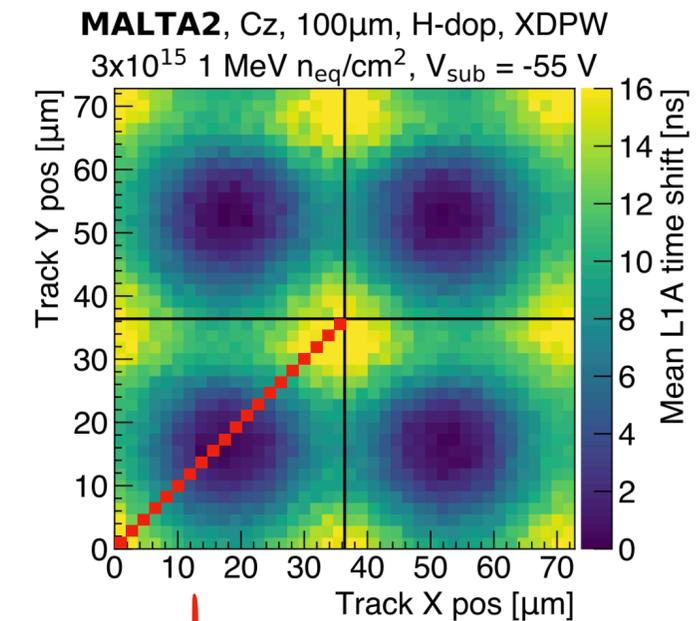
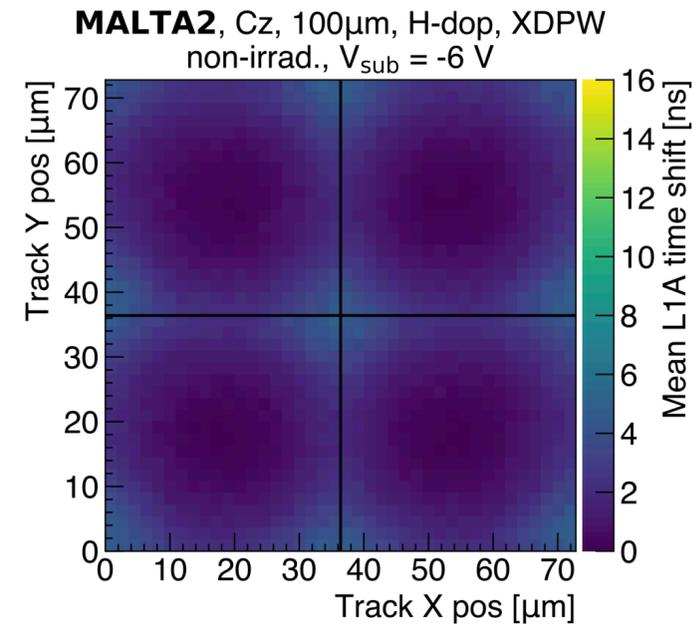
- Electronics jitter
- Time-walk
- Charge collection effects
- Scintillator jitter ($\sim 0.5 \text{ ns}$)
- FPGA readout jitter ($\sim 0.9 \text{ ns}$)

* **98% of hits collected within 25 ns**

* **90% of hits collected within 8 ns**

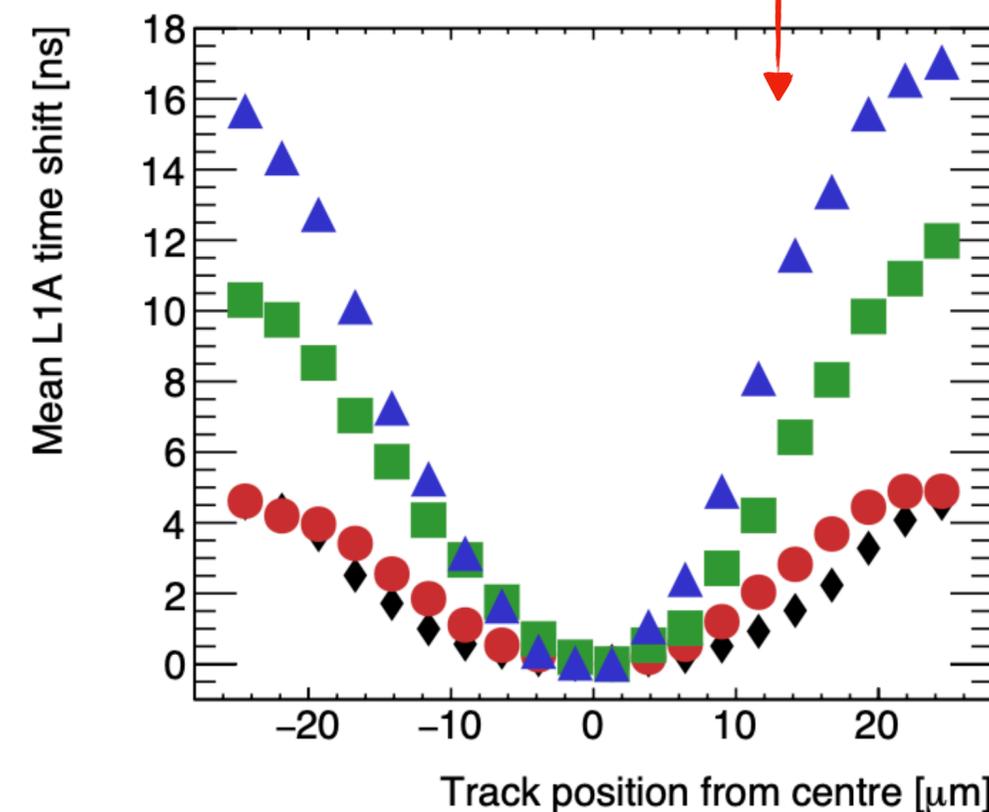
Timing - after irradiation

- * Charge trapping and changing mobility of charge carriers
- * Uniformity deteriorates as the radiation dose increases
- *Increasing the substrate voltage helps!*



MALTA2
Cz, 100 μ m
back-metal, XDPW
[1 MeV n_{eq}/cm^2]

- H-dop, 1×10^{15}
- H-dop, 2×10^{15}
- ▲ H-dop, 3×10^{15}



MALTA2
Cz, 100 μ m, H-dop
back-metal, XDPW

- ◆ non-irrad.
- 1×10^{15} 1 MeV n_{eq}/cm^2
- 2×10^{15} 1 MeV n_{eq}/cm^2
- ▲ 3×10^{15} 1 MeV n_{eq}/cm^2

Timing - after irradiation *w/ VH doping*

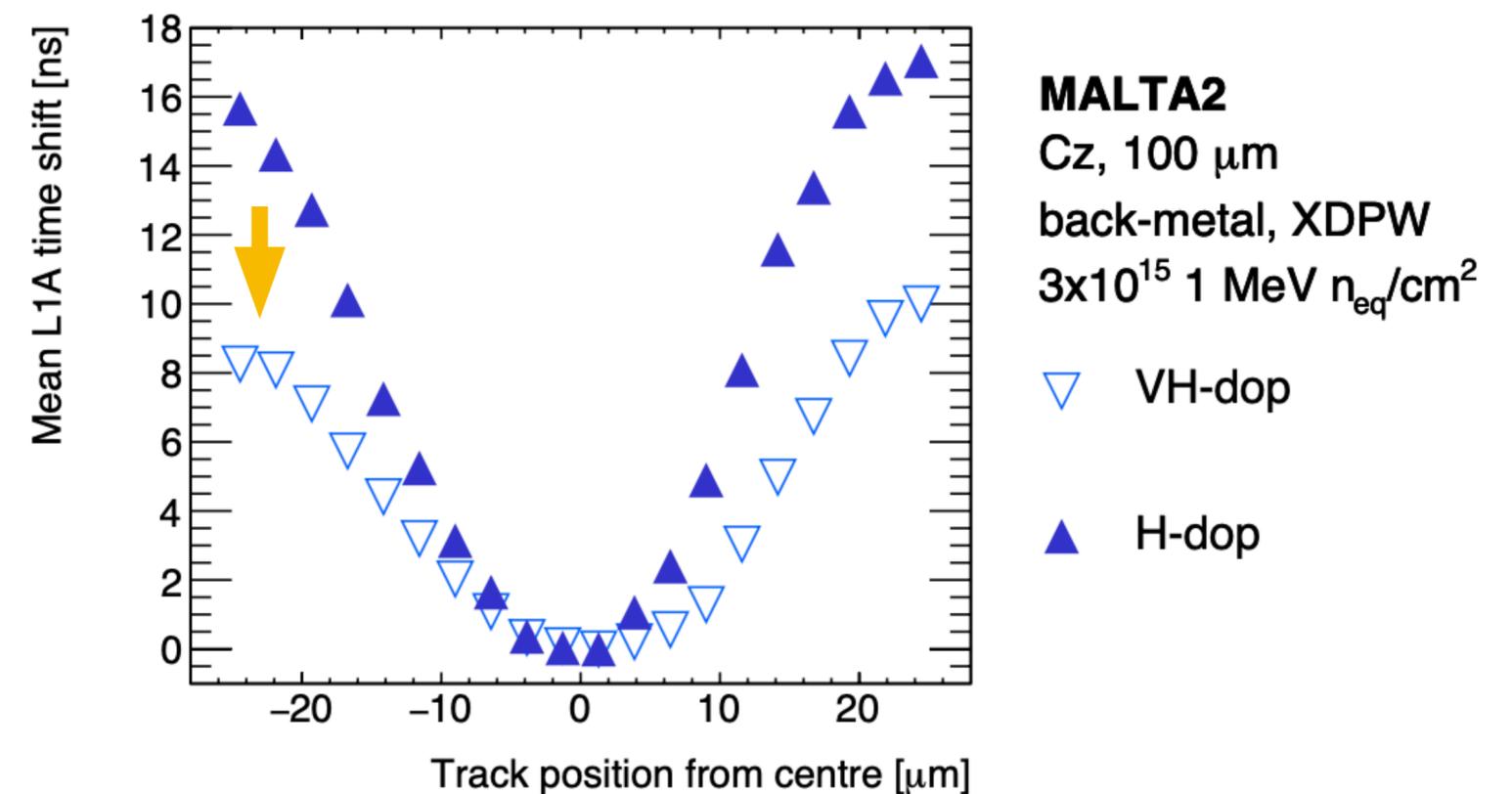
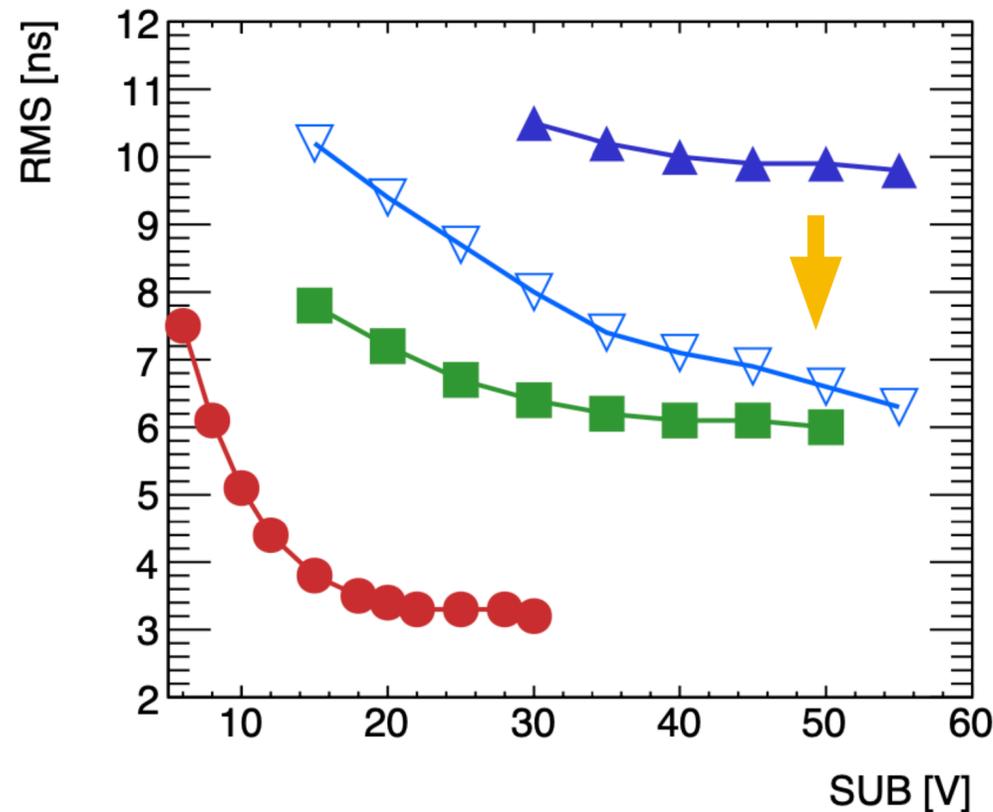
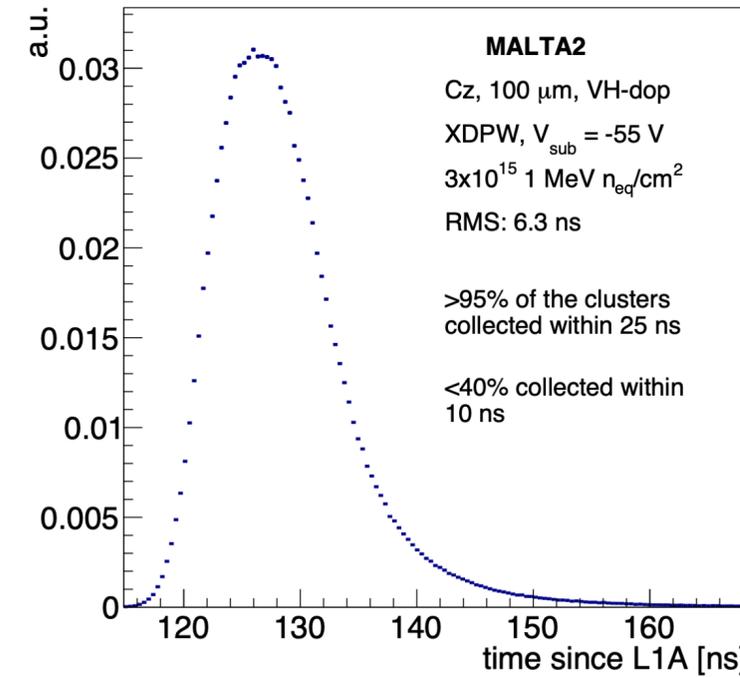


* **Higher doping** further improves the performance

▶ **95% of hits collected within 25 ns**

○ **40% of hits collected within 8 ns**

@ $3 \times 10^{15} n_{eq}/cm^2$



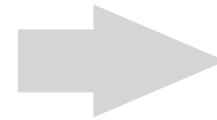
Conclusions



First **successful application** of MALTA chips as telescope planes with $\sigma_s = 4.1\mu\text{m}$ & $\sigma_t = 2.1\text{ ns}^*$

The large R&D campaign of MALTA2 brought a combination of modifications including

- ▶ pixel design
- ▶ high-resistivity Cz substrates
- ▶ backside metallisation
- ▶ high doping of the n-layer



Excellent performance up to $3 \times 10^{15} n_{\text{eq}}/\text{cm}^2$

- * 99% efficiency
- * < 40 Hz/pixel noise occupancy
- * > 95% of the clusters collected within the LHC bunch crossing window

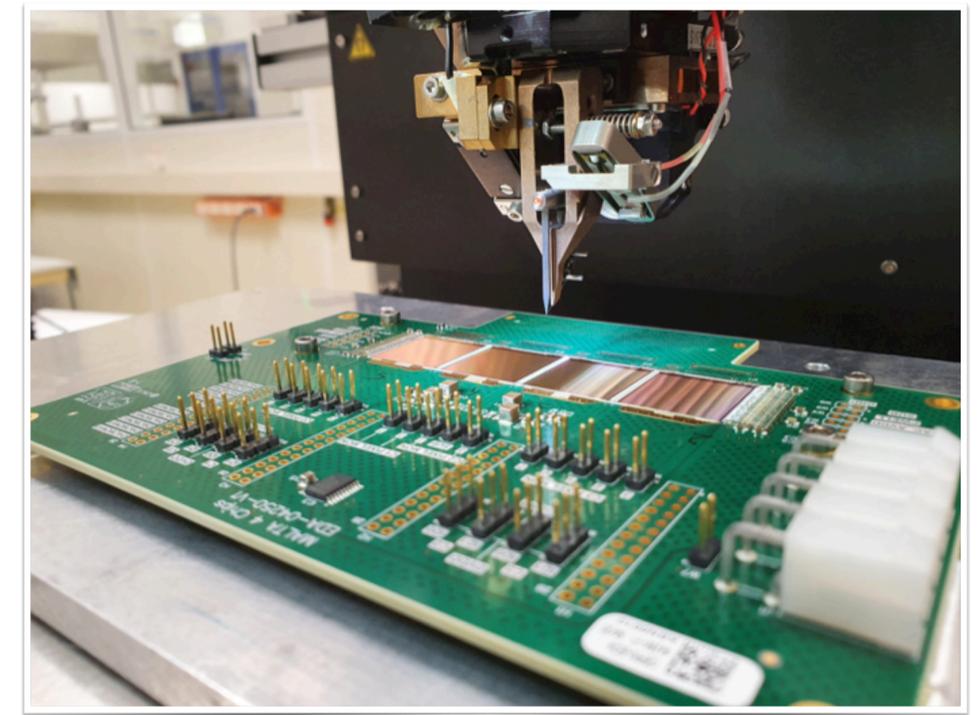
Ongoing measurements to estimate the depletion depth.

Four-chip board and flex

- * 4-chip MALTA board functionality recently demonstrated
- * tested successfully in 2023 at SPS

MALTA3 chip demonstrator under production:

- * improved in-pixel digital electronics:
 - ▶ faster signal generation
- * <1 ns time-stamping in periphery, >1 Gb/s serial output communication



BACKUP

[Radiation Hardness of MALTA2 Monolithic CMOS Sensors on Czochralski Substrates](#)

Milou van Rijnbach, Dumitru Vlad Berlea, Valerio Dao, Martin Gaži et al.

e-Print: [2308.13231](#) [physics.ins-det]

[Performance of the MALTA telescope](#)

Milou van Rijnbach, Giuliano Gustavino et al.

e-Print: [2304.01104](#) [hep-ex]

DOI: [10.1140/epjc/s10052-023-11760-z](#)

Published in: Eur.Phys.J.C 83 (2023) 7, 581

[MALTA-Cz: a radiation hard full-size monolithic CMOS sensor with small electrodes on high-resistivity Czochralski substrate](#)

H. Pernegger et al.

e-Print: [2301.03912](#) [physics.ins-det]

DOI: [10.1088/1748-0221/18/09/P09018](#) (publication)

Published in: JINST 18 (2023) 09, P09018

[Mini-MALTA: Radiation hard pixel designs for small-electrode monolithic CMOS sensors for the High Luminosity LHC](#)

M. Dyndal, V. Dao et al.

e-Print: [1909.11987](#) [physics.ins-det]

DOI: [10.1088/1748-0221/15/02/P02005](#)

Published in: JINST 15 (2020) 02, P02005

[Simulations of CMOS pixel sensors with a small collection electrode, improved for a faster charge collection and increased radiation tolerance](#)

Magdalena Munker(CERN) et al.

e-Print: [1903.10190](#) [physics.ins-det]

DOI: [10.1088/1748-0221/14/05/C05013](#)

Published in: JINST 14 (2019) 05, C05013

[A \$1\ \mu\text{W}\$ Radiation-Hard Front-End in a \$0.18\text{-}\mu\text{m}\$ CMOS Process for the MALTA2 Monolithic Sensor](#)

F. Piro et al.

DOI: [10.1109/TNS.2022.3170729](#) , [10.36227/techrxiv.19222311.v1](#)

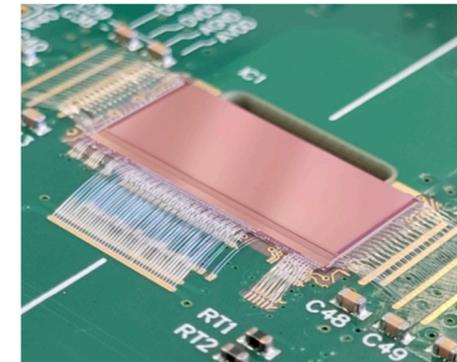
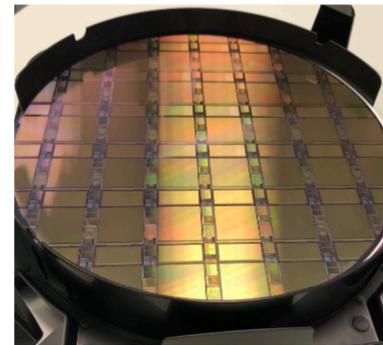
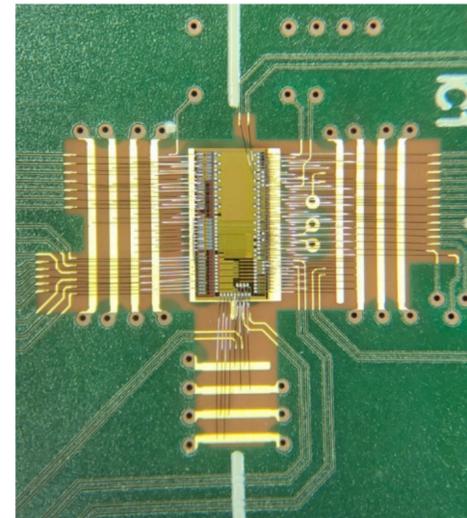
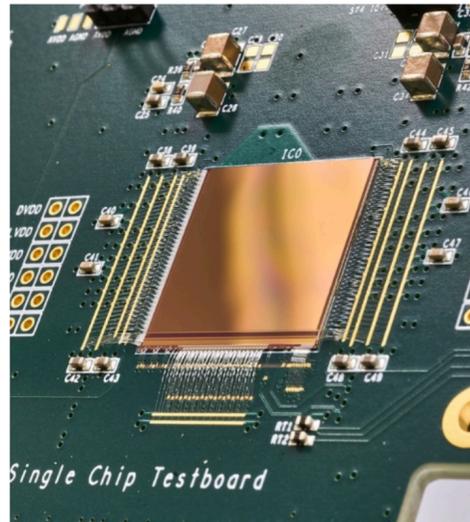
Published in: IEEE Trans.Nucl.Sci. 69 (2022) 6, 1299-1309

MALTA history



STREAM

AIDA Innova WP5 and
CERN EP R&D WP 1.2



MALTA1 & MLVL

Mini-MALTA

MALTA C

MALTA 2

MALTA 3

Jan 2018

Jan 2019

Aug 2019

Jan 2021

2023

Large demonstrator
Asynchronous readout
Electrode size and reset
mechanism evaluation

Small demonstrator
Process and mask
modification

Slow control
improvements on EPI
and Czochralski
substrates

New front-end
Additional process
modification

Large matrix
Time tagging

Poor lateral field after
irradiation

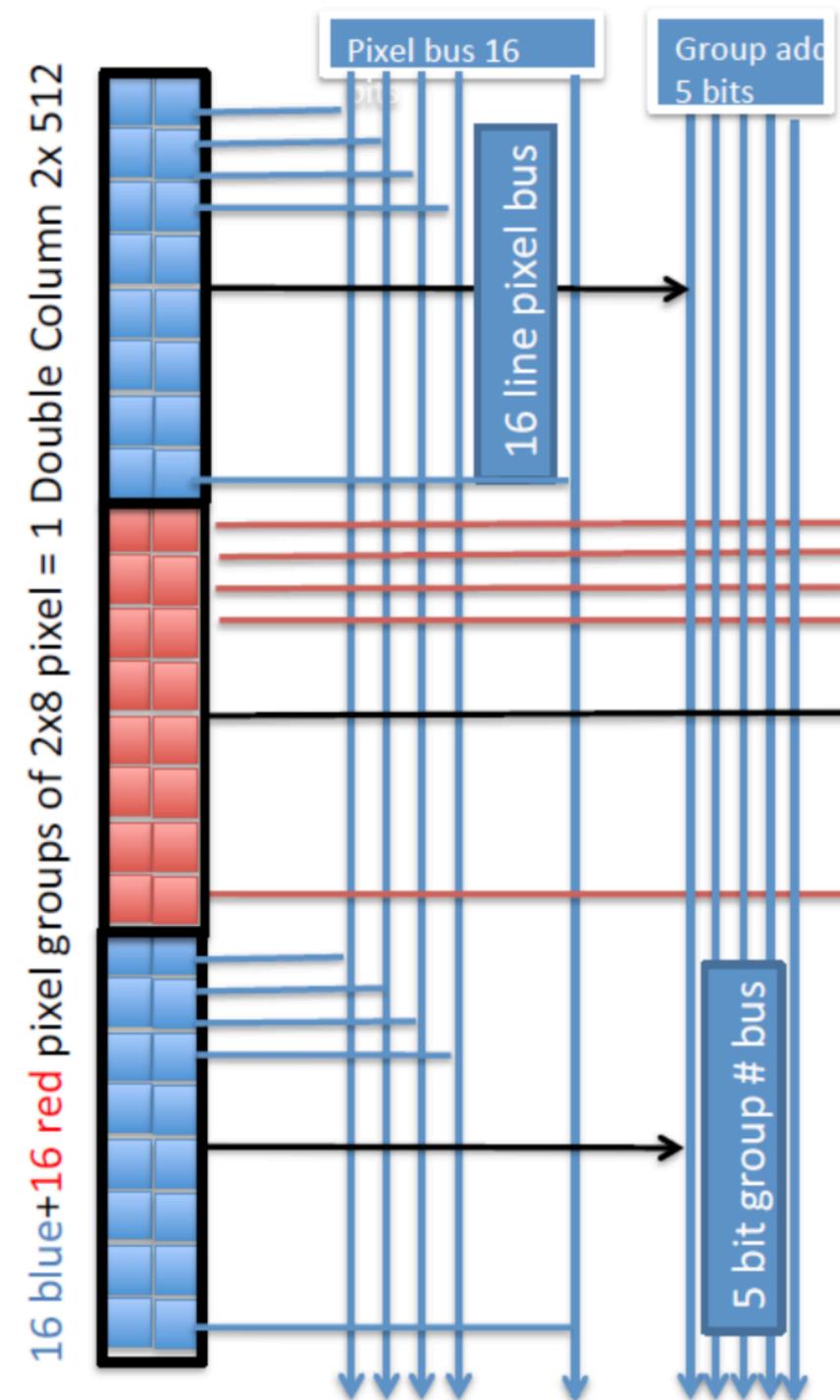
Full efficiency after
 $1e15$ n/cm²

Enlarged cluster size and
improved time resolution
on Czochralski

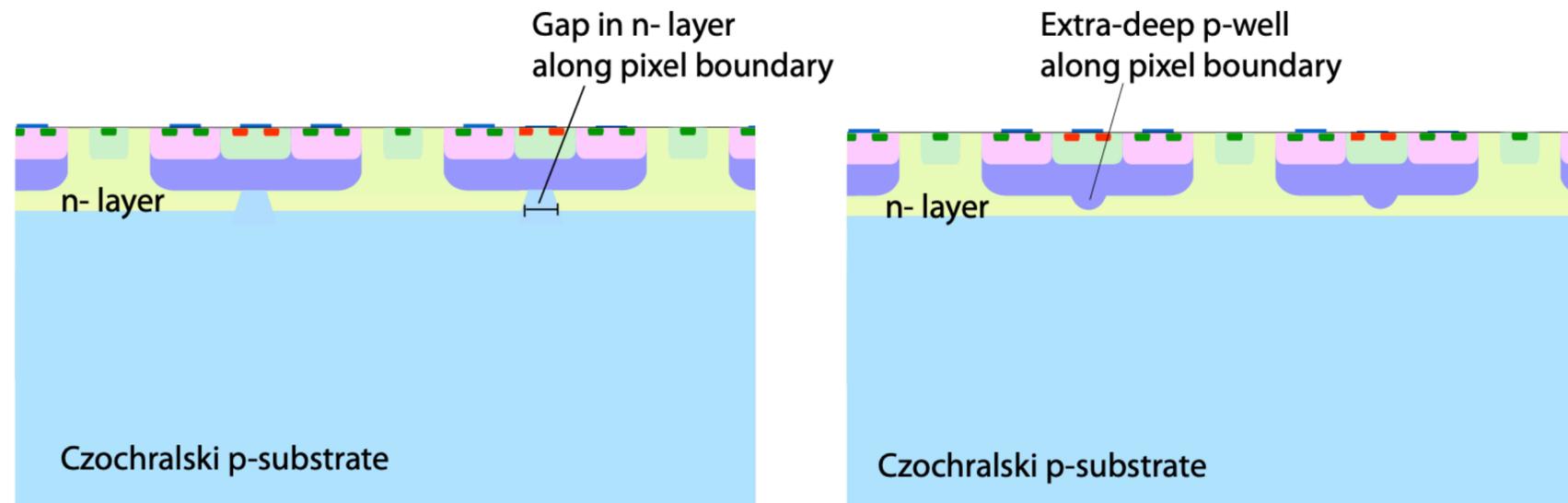
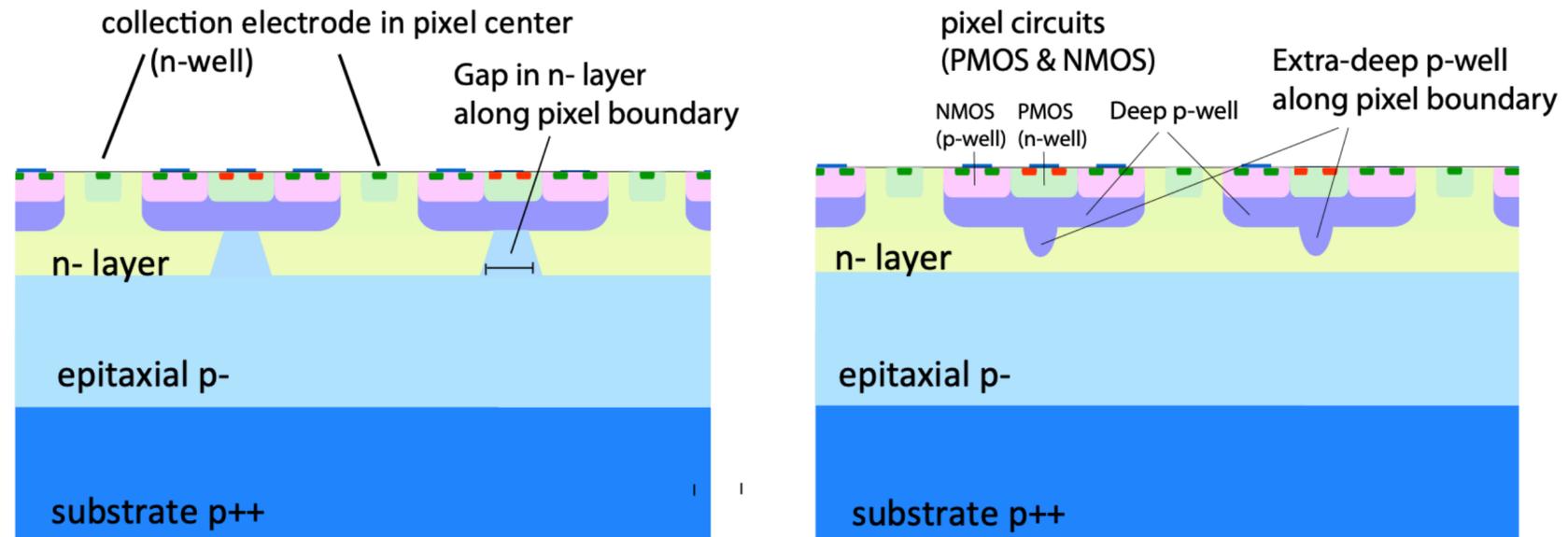
Improved time resolution
and on chip synchronization

MALTA read-out architecture

- * Novel asynchronous readout architecture for **high hit rate capability**:
 - ▶ data transmitted *asynchronously* (no clock) over to end of column
 - ▶ latency: ~ **few ns**
 - ▶ output rate: **>>100 MHz**
 - ▶ **hit coordinates transmitted through 37 parallel output signals**



Czochralski geometry



MALTA Telescope - specifications



MALTA Telescope Planes						
Plane	1	2	3	4	5	6
Specifications						
Substrate Type	Epi	Cz	Cz	Cz	Cz	Epi
Sensor Flavour	STD	NGAP	STD	STD	NGAP	STD
Total Thickness [μm]	100	100	300	300	100	300
Operation Voltage [V]	-6	-6	-30	-30	-6	-6
Distance [cm]	0	8	16	94	102	110

Characterisation of Telescope Planes						
Plane	1	2	3	4	5	6
Average Efficiency [%]	97.4 \pm 0.1	96.9 \pm 0.1	99.2 \pm 0.1	99.0 \pm 0.1	95.0 \pm 0.1	94.0 \pm 0.1
Average number of hits per event	1.7 \pm 0.9	1.8 \pm 1.0	2.2 \pm 1.1	2.5 \pm 1.2	1.7 \pm 0.9	1.6 \pm 0.9
Average Cluster Size [pixels]	1.1 \pm 0.3	1.1 \pm 0.4	1.7 \pm 0.8	1.9 \pm 0.9	1.1 \pm 0.3	1.1 \pm 0.4

2nd prototype of MALTA family

* Improved FE:

▶ enlarged transistors & cascode stage

● lower noise & higher gain

☑ enables operating the chip at lower threshold (down to $O(100)$ e⁻)

☑ increases sensitivity to small signal

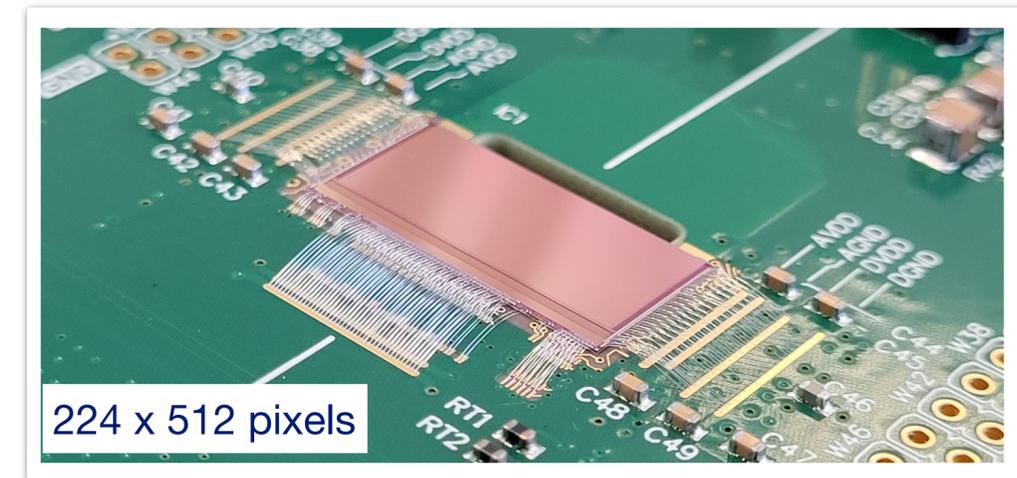
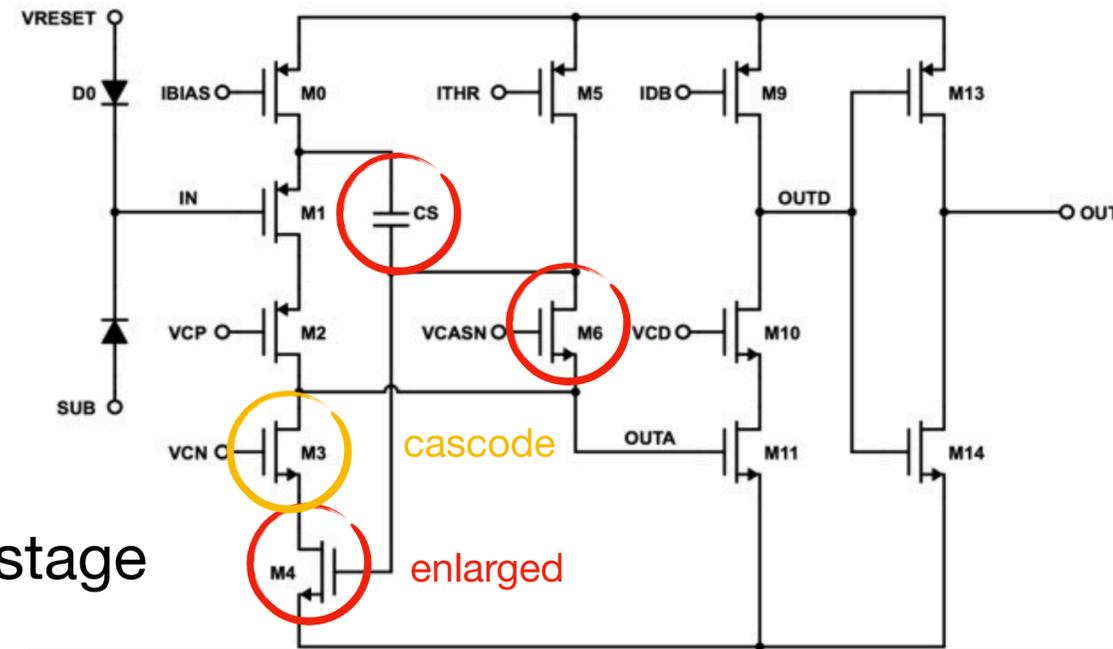
○ higher radiation tolerance

● with same configuration (Ref. *JINST 15 (2020) 02*)

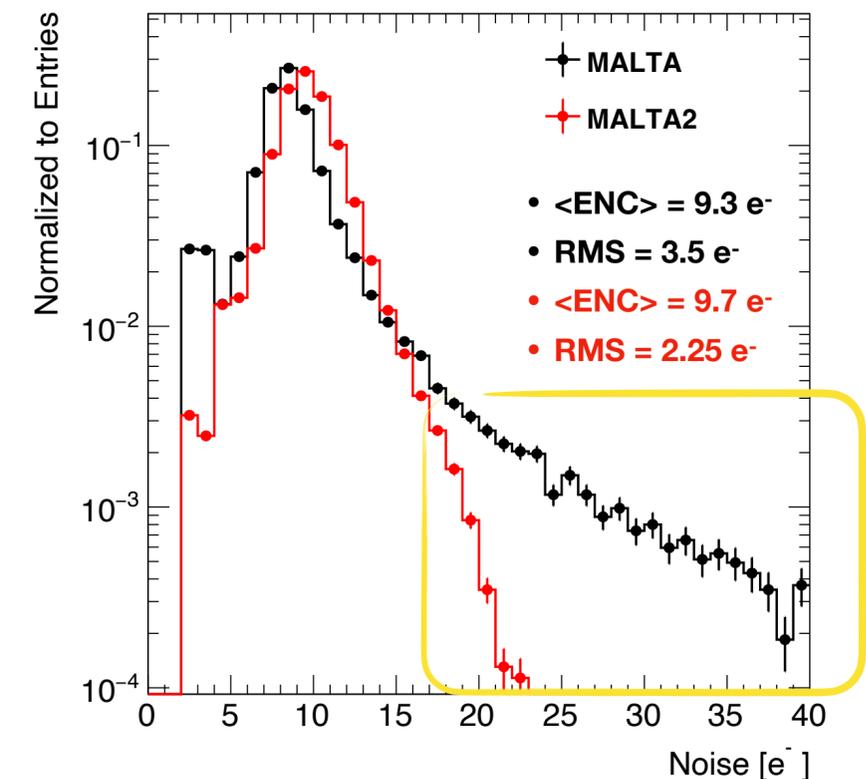
std. transistors: thr = 340 el., enlarged transistors = 200 el.

eff @ 1×10^{15} n_{eq}/cm²: std transistors=87%, enlarged transistors =98%

☑ improve speed of analog FE



Malta2 public plots



Comparison of MALTA & MALTA2 at compatible threshold (~340 e⁻)

MALTA2 Timing: Front End



Time-walk of FE measured using special pixels with analog output monitoring.

- * time for amplifier output to reach discriminator threshold, depends on charge deposition.

Sensor exposed to ^{90}Sr source

- MIP-like signals, avg. deposition $\sim 1800 e^-$

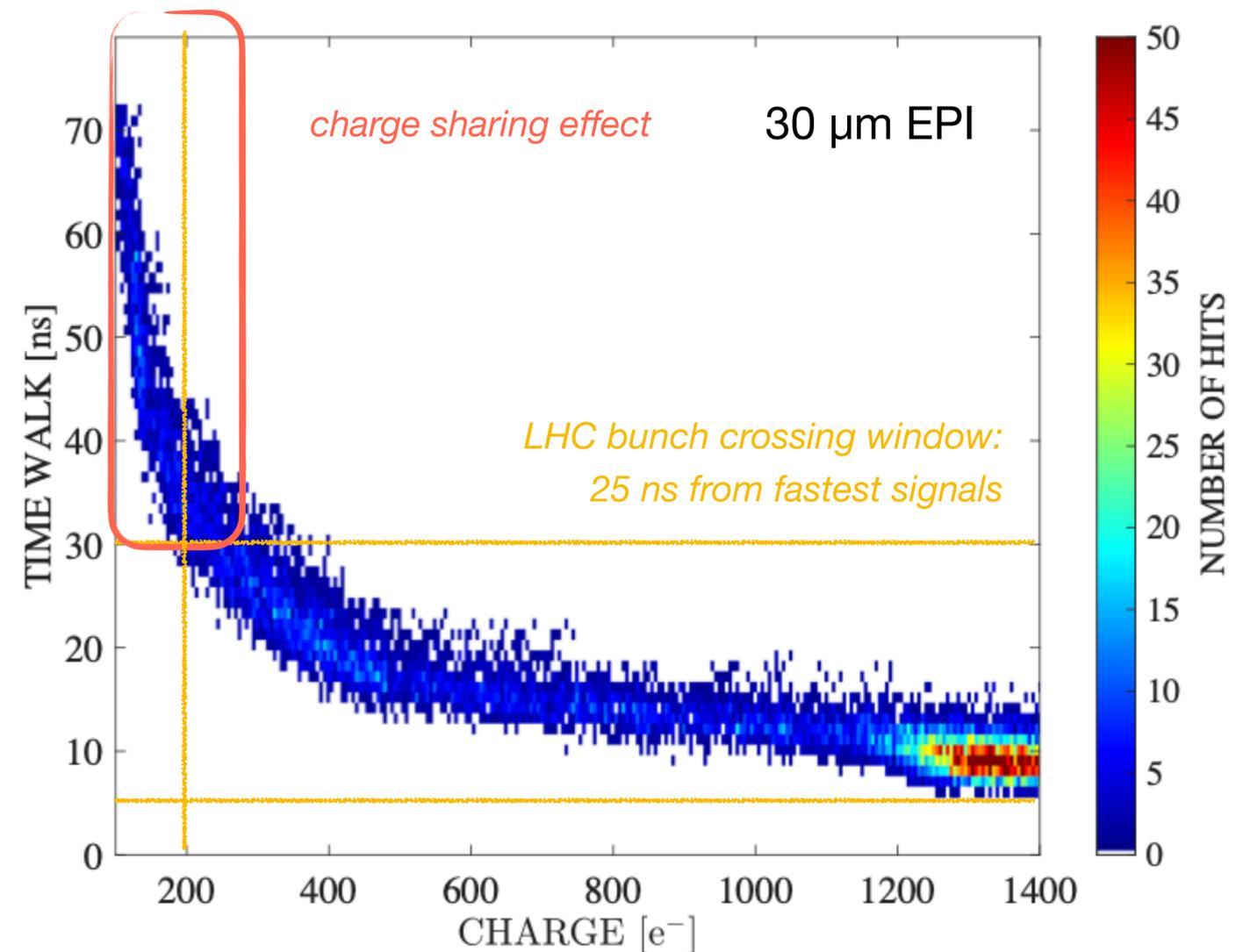
- * **90% of hits arrive within 25 ns window**

- ▶ **in-time threshold $\Rightarrow \sim 200 e^-$**

- * largest deposited charges \Rightarrow time-walk ~ 10 ns.

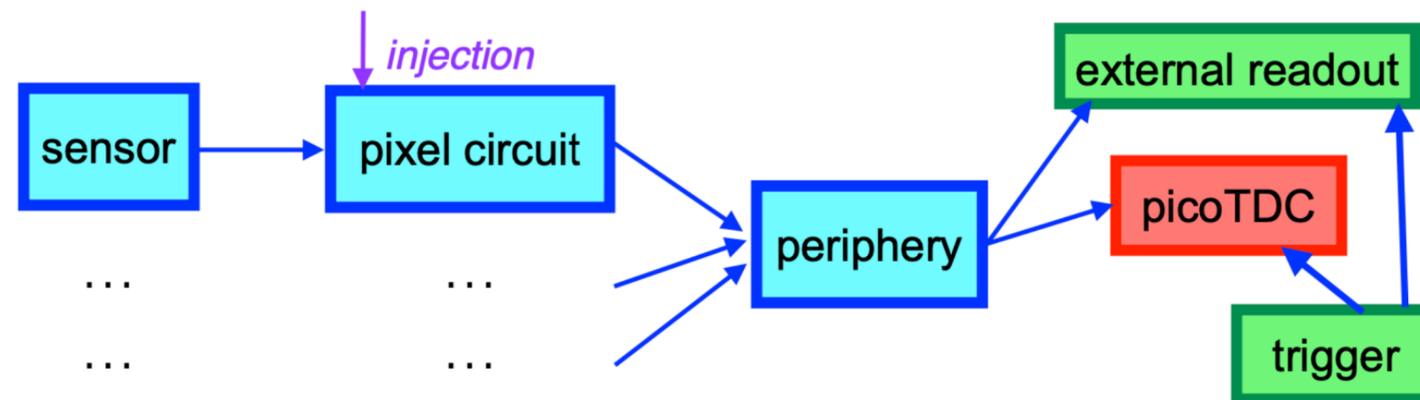
- * small charge deposition attributed to charge-sharing effects

- ▶ small signals from pixel corners arrives later



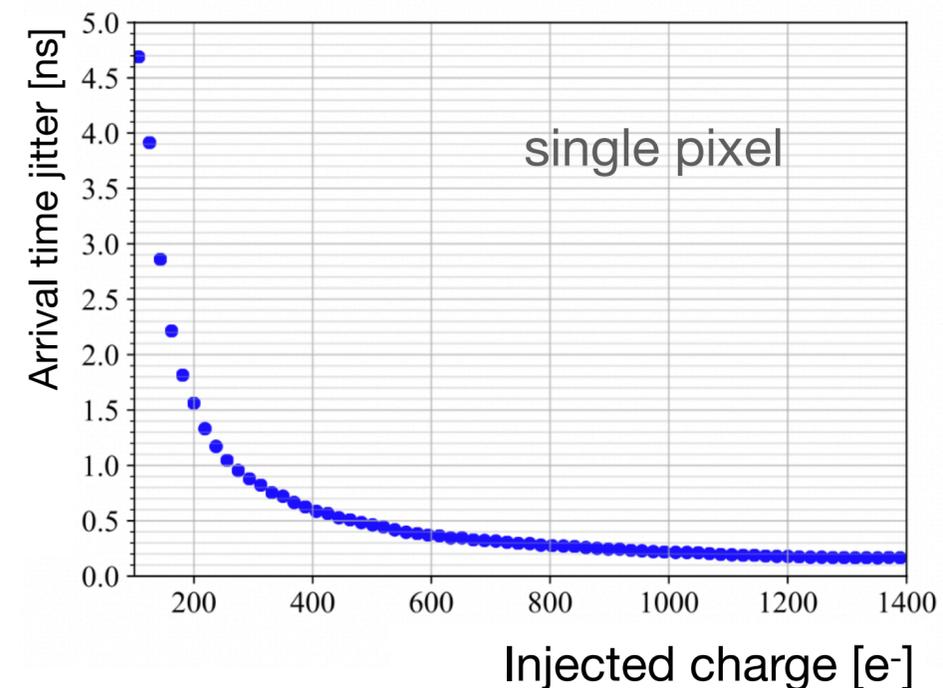
Set of measurements to isolate individual contributions:

- * in-pixel charge injection
- * chip interfaced with picoTDC (3 ps resolution)



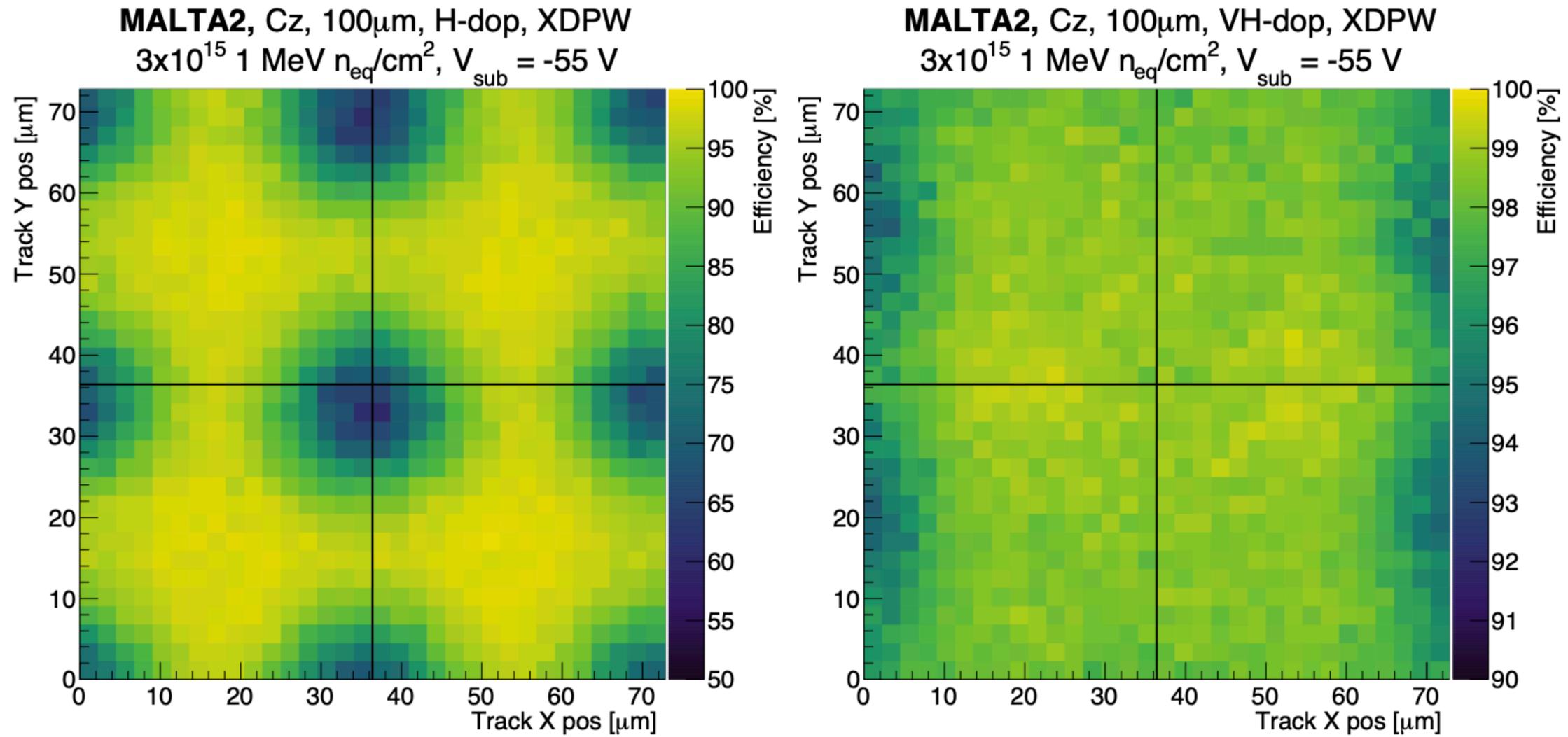
Measuring time jitter dominated by FE*

- * varying between 4.7 (100 e⁻) to 0.16 ns (> 1200 e⁻) as injected charge increases
 - ▶ 500 ps for 500 e⁻
- * uniform response across the entire chip

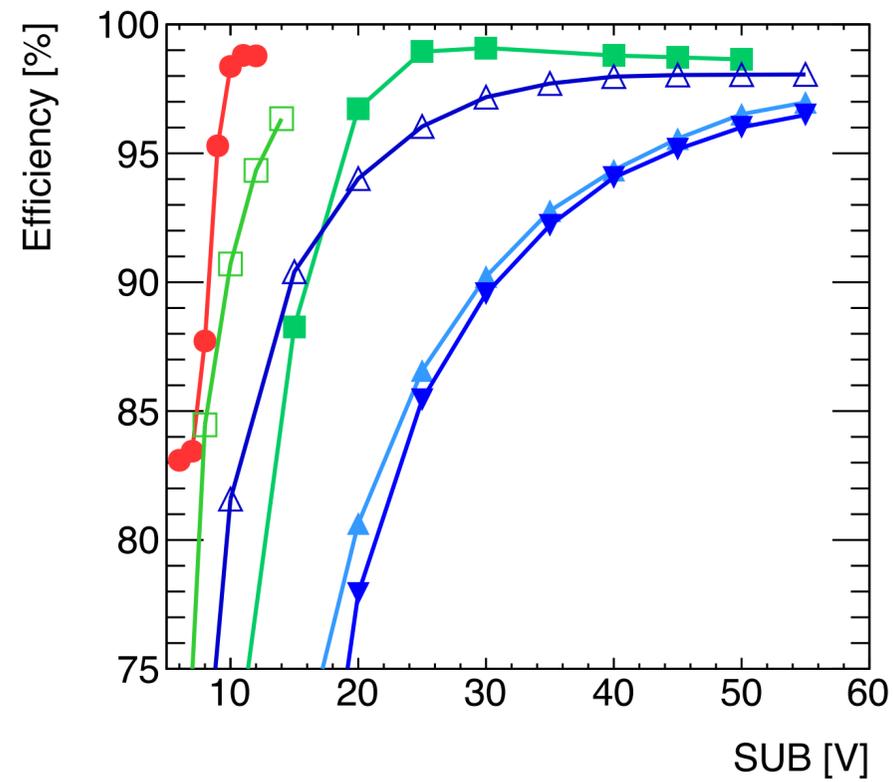


*time jitter of the reference pulse is < 100 ps

In-pixel efficiency

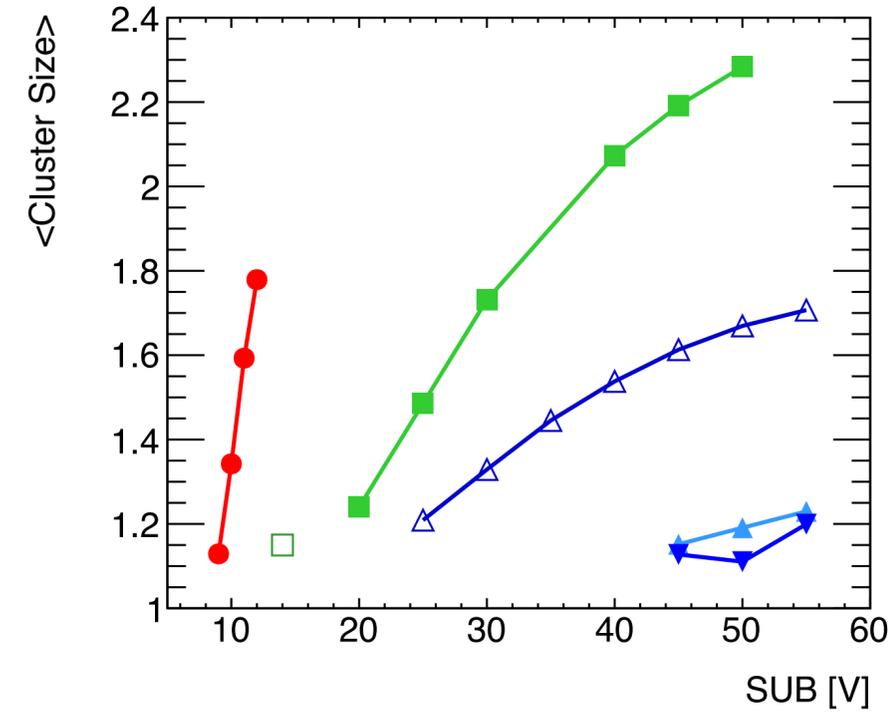


Summary plots



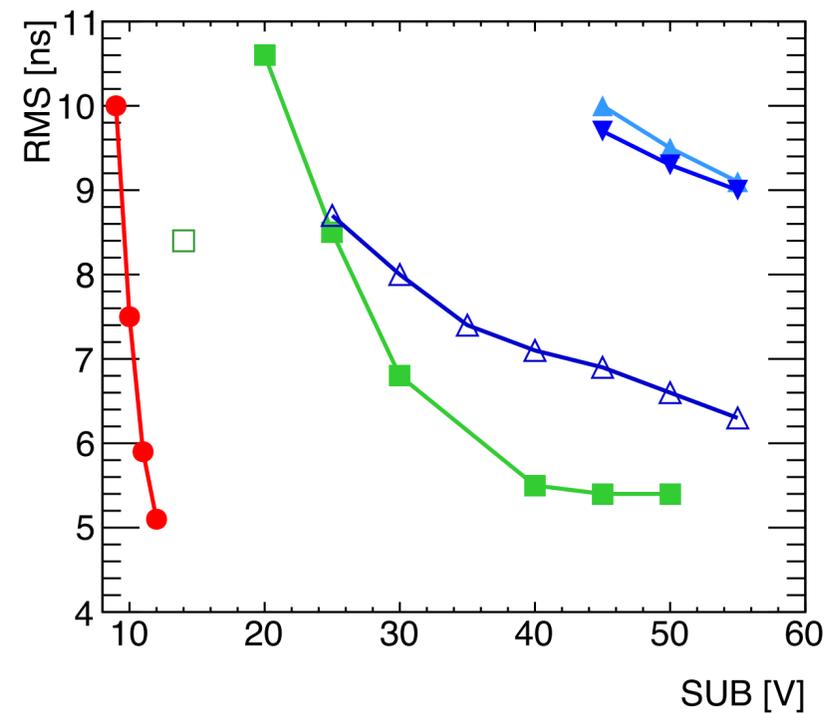
MALTA2
CZ Irradiated Samples [$1 \text{ MeV } n_{\text{eq}}/\text{cm}^2$]

- 1E15, Fiducial Area, Conductive Glue
- 2E15, Fiducial Area, Conductive Glue
- 2E15, Full Chip, Backside Metallization
- △ 3E15, Full Chip, Backside Metallization
- ▲ 3E15, Fiducial Area, Regular Backside
- ▼ 3E15, Fiducial Area, Regular Backside



MALTA2
CZ Irradiated Samples [$1 \text{ MeV } n_{\text{eq}}/\text{cm}^2$]

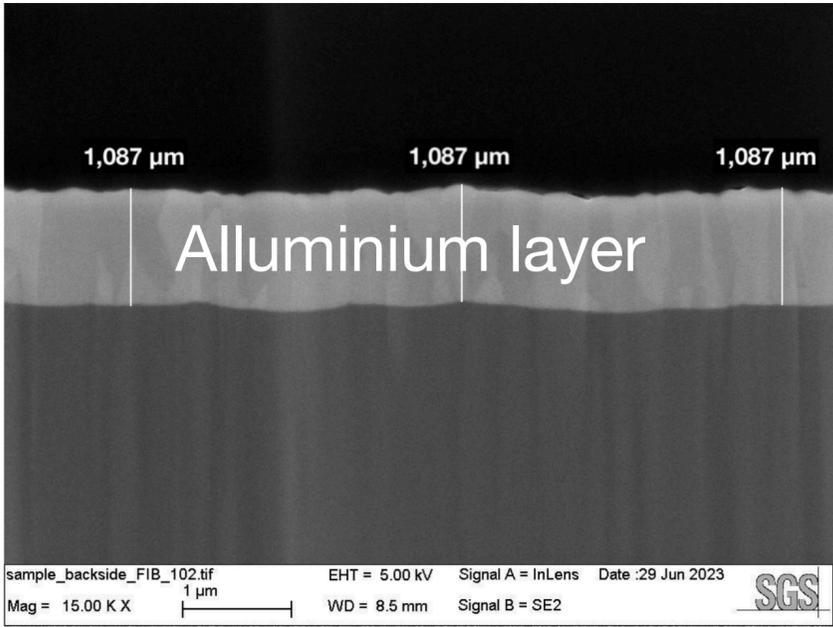
- 1E15, Fiducial Area, Conductive Glue
- 2E15, Fiducial Area, Conductive Glue
- 2E15, Full Chip, Backside Metallization
- △ 3E15, Full Chip, Backside Metallization
- ▲ 3E15, Fiducial Area, Regular Backside (1)
- ▼ 3E15, Fiducial Area, Regular Backside (2)



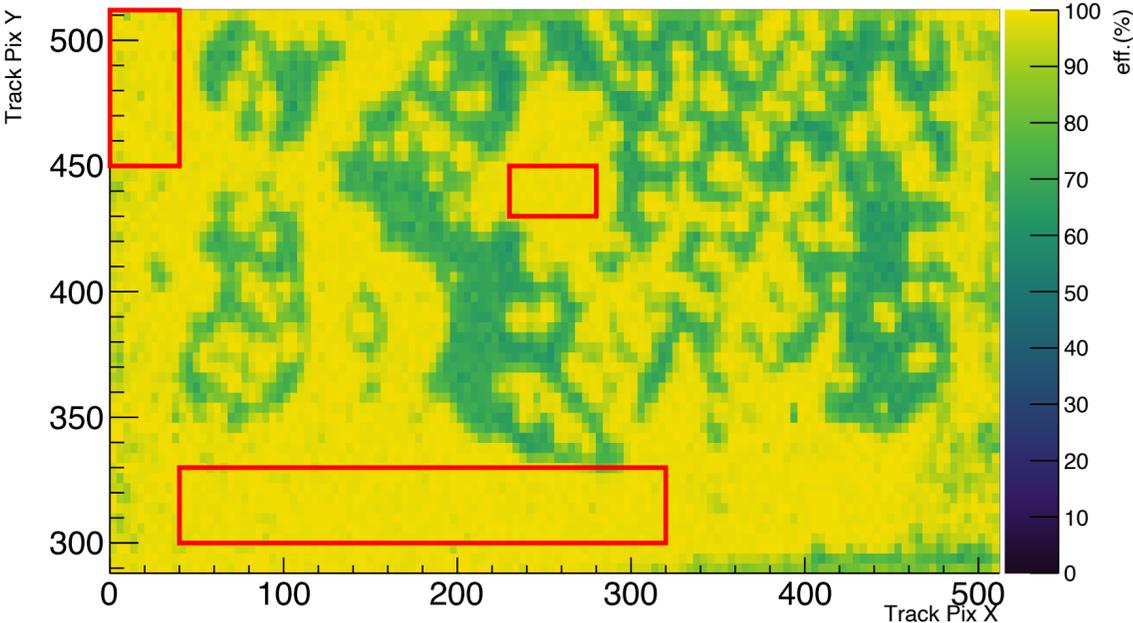
MALTA2
CZ Irradiated Samples [$1 \text{ MeV } n_{\text{eq}}/\text{cm}^2$]

- 1E15, Fiducial Area, Conductive Glue
- 2E15, Fiducial Area, Conductive Glue
- 2E15, Full Chip, Backside Metallization
- △ 3E15, Full Chip, Backside Metallization
- ▲ 3E15, Fiducial Area, Regular Backside (1)
- ▼ 3E15, Fiducial Area, Regular Backside (2)

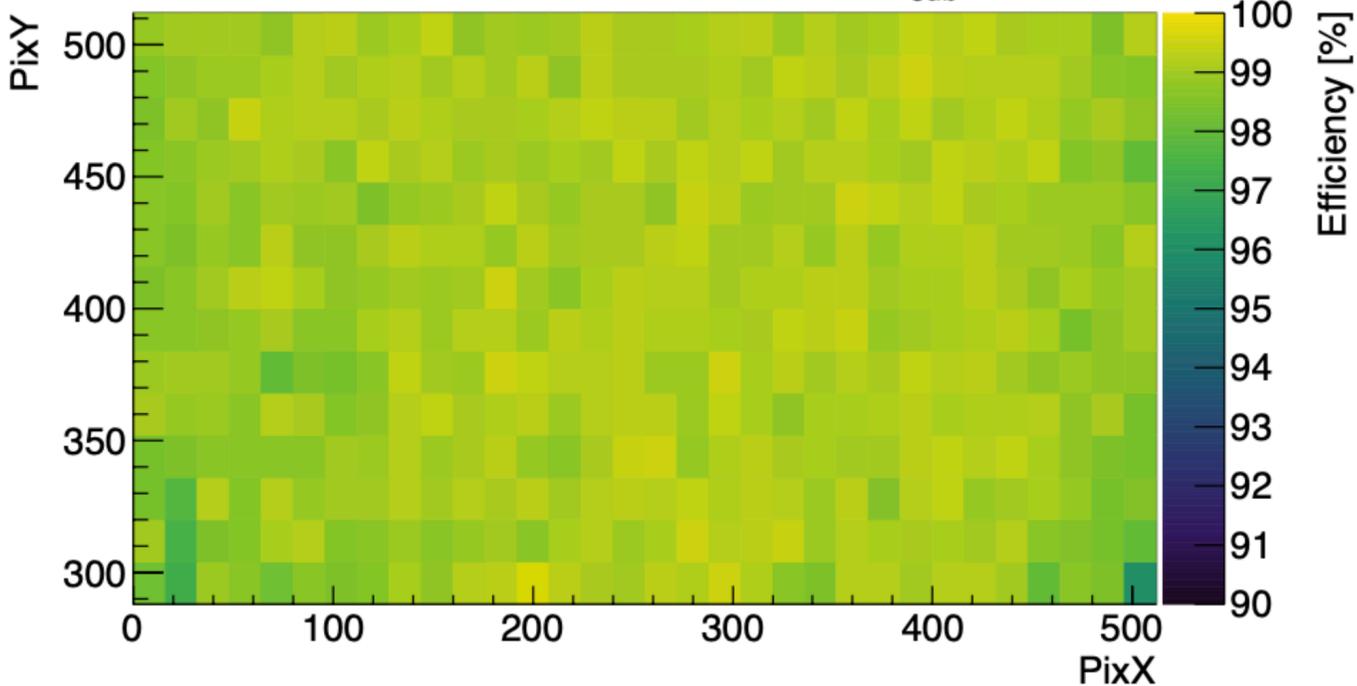
Back Metallisation



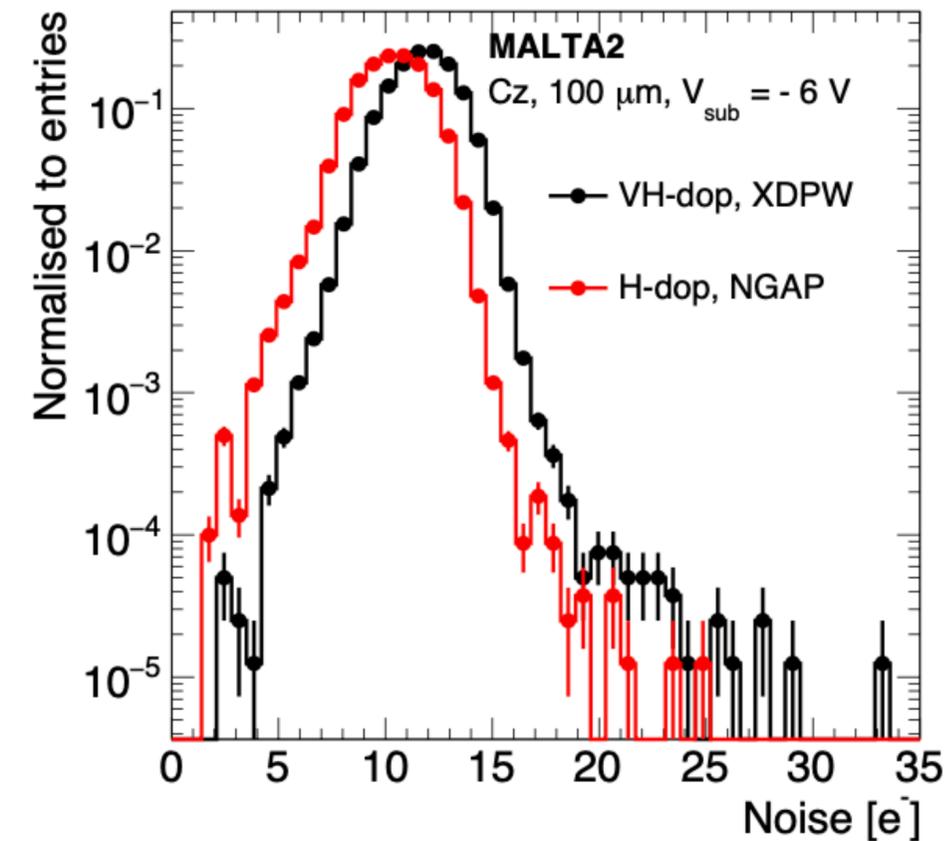
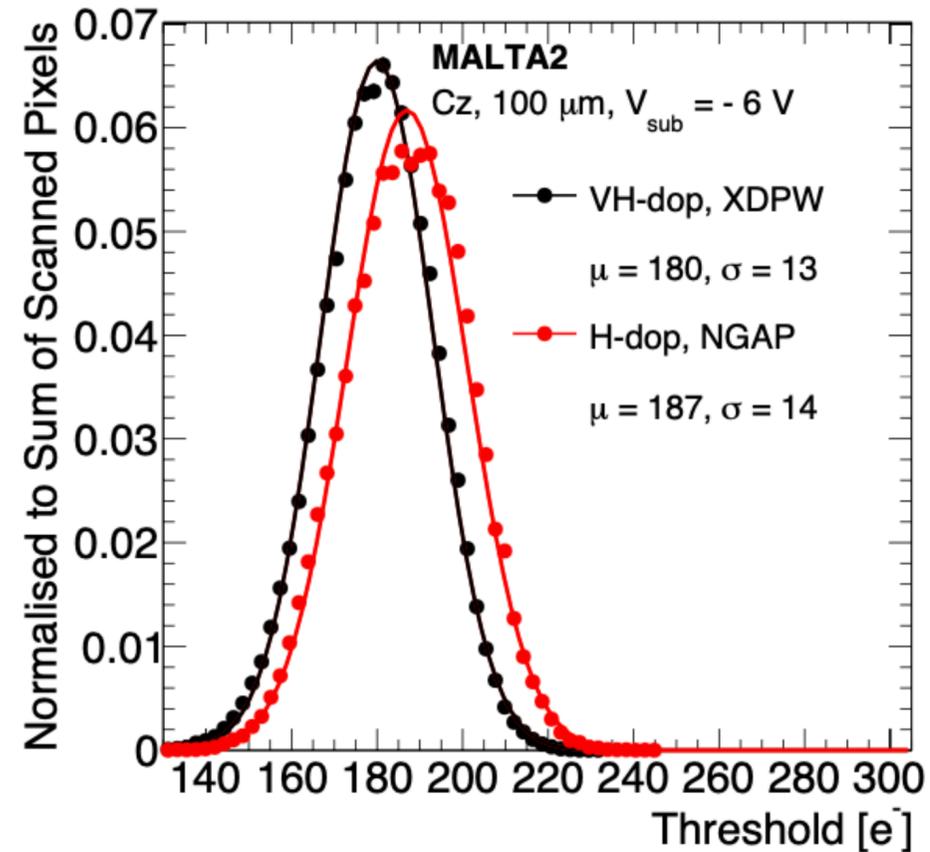
MALTA2, Cz, 100 μm , H-dop, NGAP
conductive glue, 10^{15} 1 MeV $n_{\text{eq}}/\text{cm}^2$, $V_{\text{sub}} = -12$ V



MALTA2, Cz, 100 μm , VH-dop, XDPW
back-metal, 10^{15} 1 MeV $n_{\text{eq}}/\text{cm}^2$, $V_{\text{sub}} = -15$ V



High vs Very High n- doping layer



Larger noise is observed for the MALTA2 with the very high doping of the n- layer.

- This effect is correlated to the **increase in capacitance due to the thinner depletion zone** around the collection electrode for a higher doped n- layer